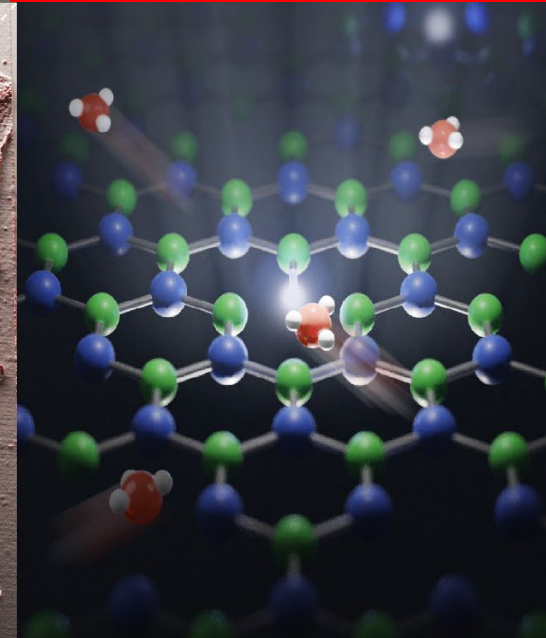
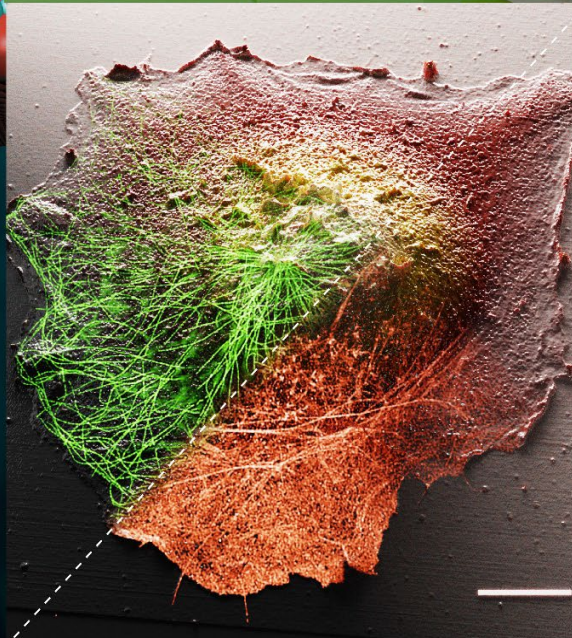
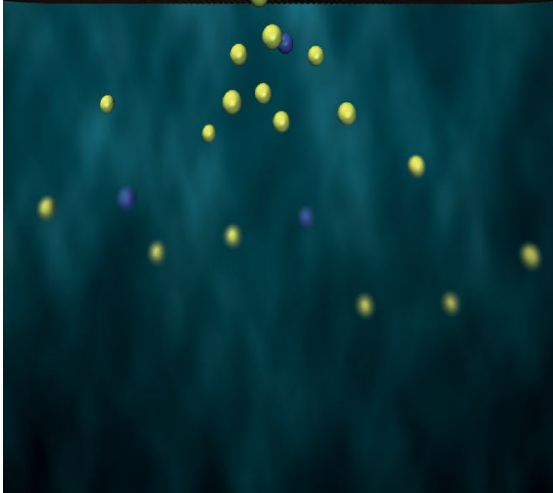
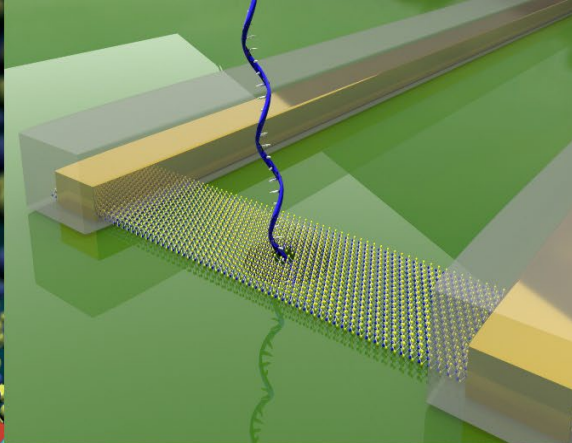
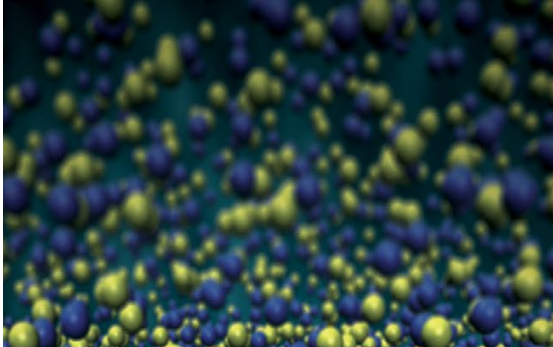


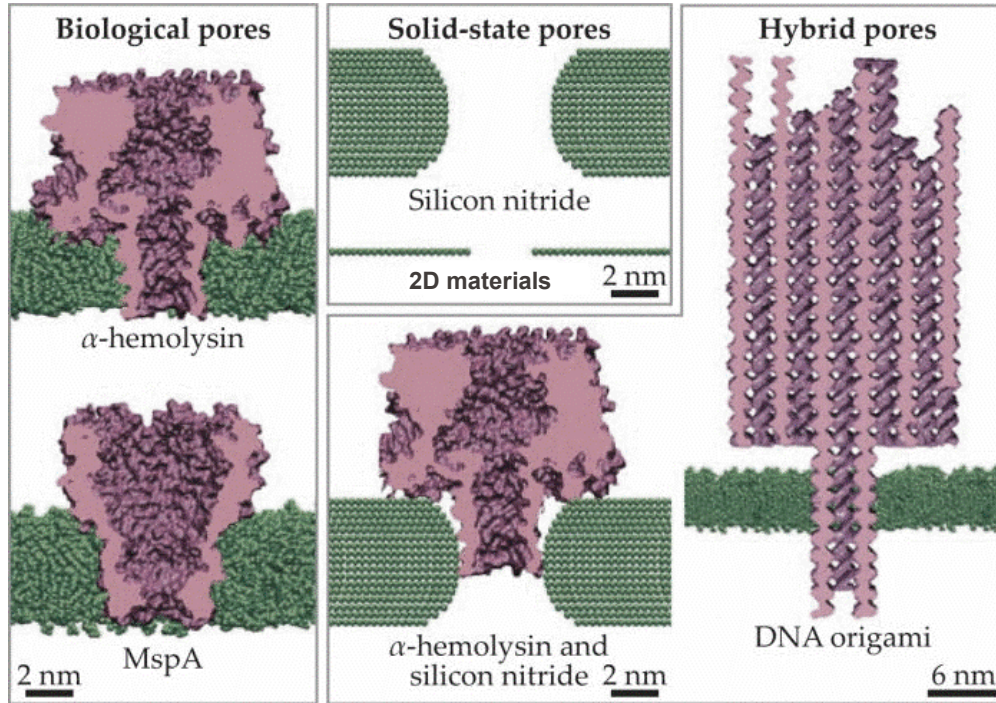
Prof. Aleksandra Radenovic

*Institute of Bioengineering, École
Polytechnique Fédérale de Lausanne
(EPFL), 1015, Lausanne, Switzerland*

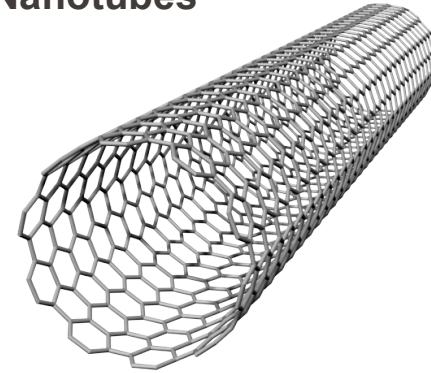
Solid state nanopores from fab to lab



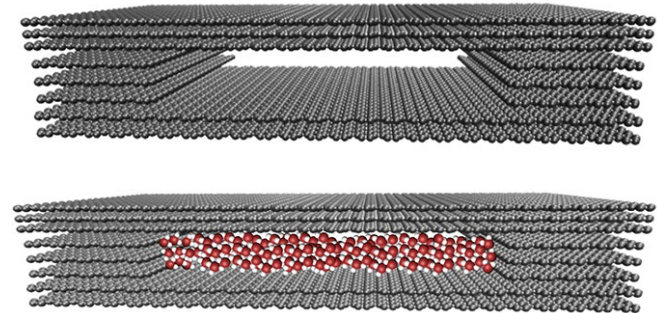
Nanopores



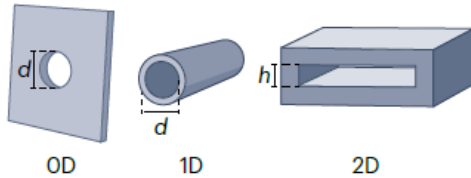
Nanotubes



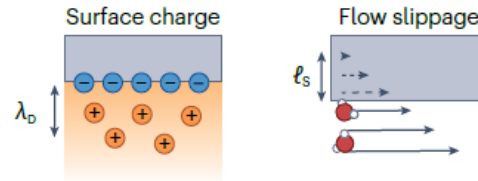
Angstrom-scale slits



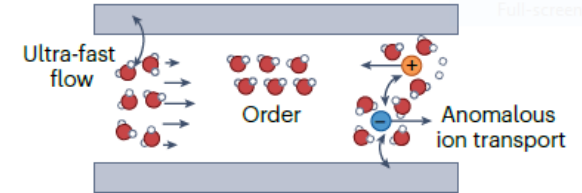
a Confinement



b Surface effects

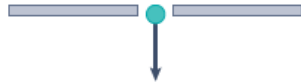


c Novel phenomena



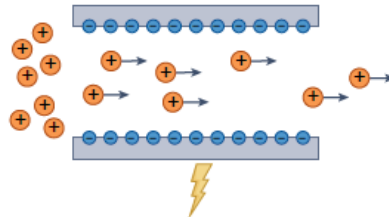
d Applications

Analyte changes the conductance when passing through the pore

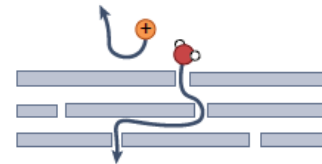


Analyte sensing

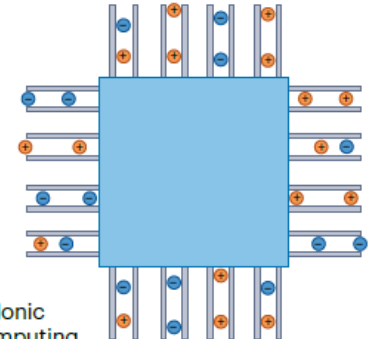
Concentration gradient is converted into ionic current



Osmotic energy harvesting



Membranes for desalination/filtration/energy



Ionic computing

Emmerich, T., Ronceray, N., Agrawal, K. V., Garaj, S., Kumar, M., Noy, A., & Radenovic, A. (2024).

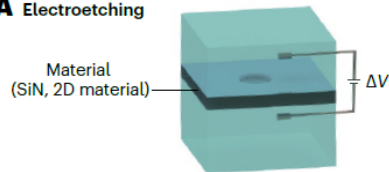
Nanofluidics. *Nature Reviews Methods Primers*, 4(1), 6.

EPFL Nanofluidics

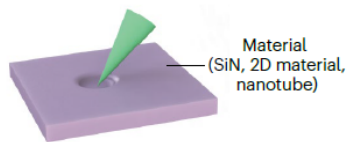
■ Emmerich, T., Ronceray, N., Agrawal, K. V., Garaj, S., Kumar, M., Noy, A., & Radenovic, A. (2024). Nanofluidics. *Nature Reviews Methods Primers*, 4(1), 6.

Removing material

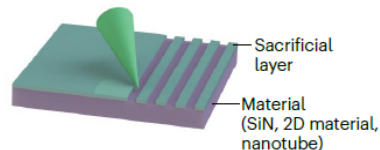
A Electroetching



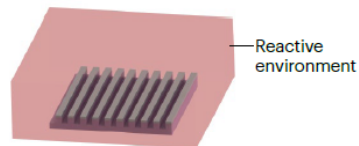
B Direct etching (FIB/EBIE/track etching)



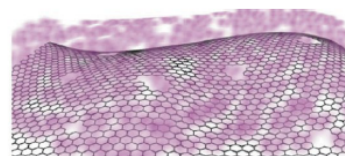
Ca E-beam lithography



Cb Reactive ion etching

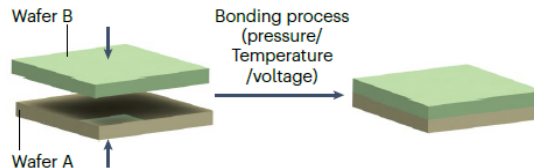


D Chemical etching

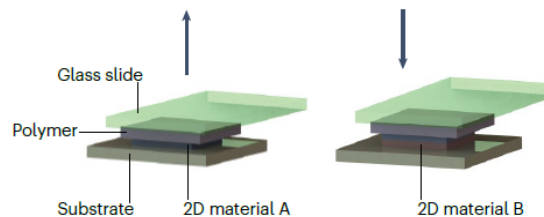


Assembling material

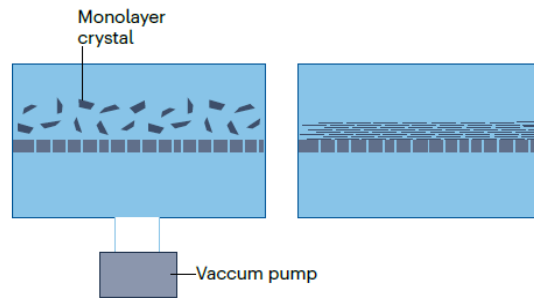
E Wafer bonding



F van der Waals assembly

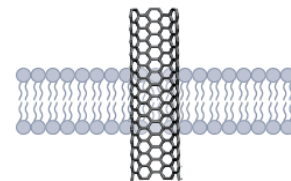


G 2D material membrane self-assembly



Embedding nanostructures

H Carbon nanotube porin in lipid bilayer



I Carbon nanotube welded into a nanopore

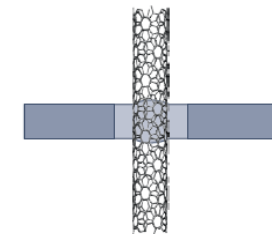


Fig. 2 | Fabrication approaches for nanofluidic devices. A, In situ electro-

Through transfer with polymeric stamps, 2D materials can be stacked on top

Huge Potential of Nanopore Device

Bio Sensors



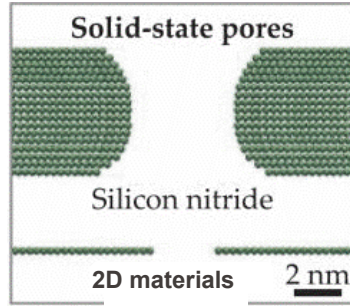
Ionic Resources



Blue Energy



Nanopores

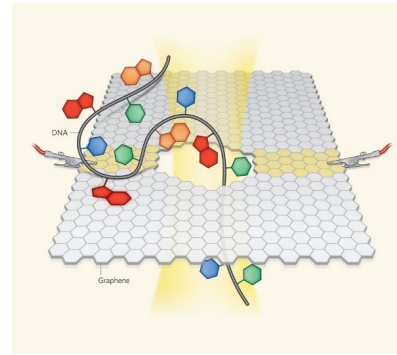
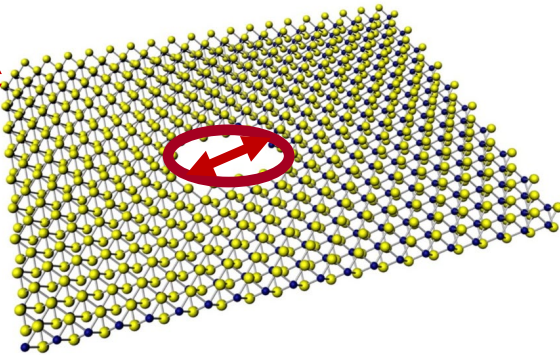


molybdenum disulfide (MoS₂)

$L=0.7\text{ nm}$

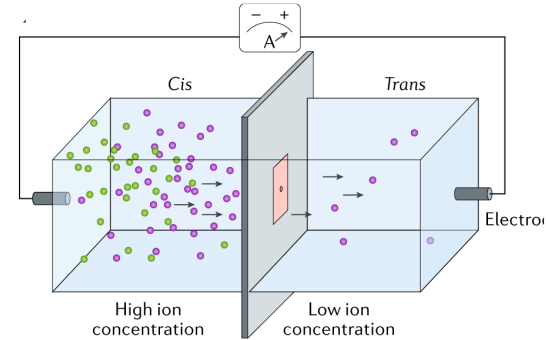
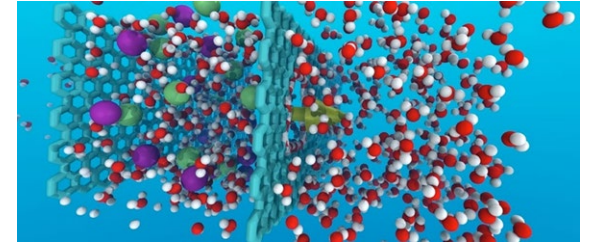


$d=\text{tunable}$

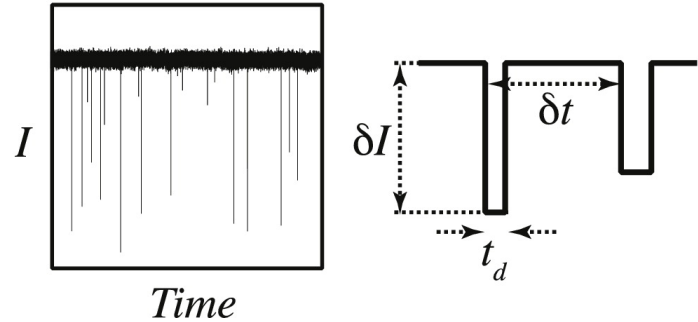
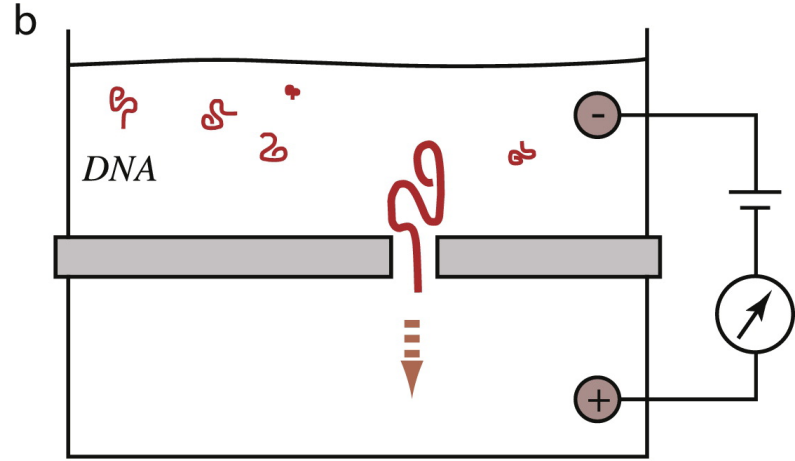
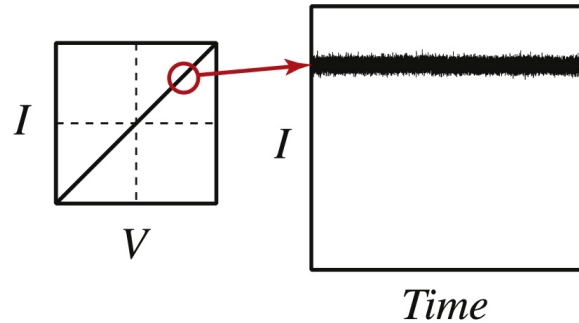
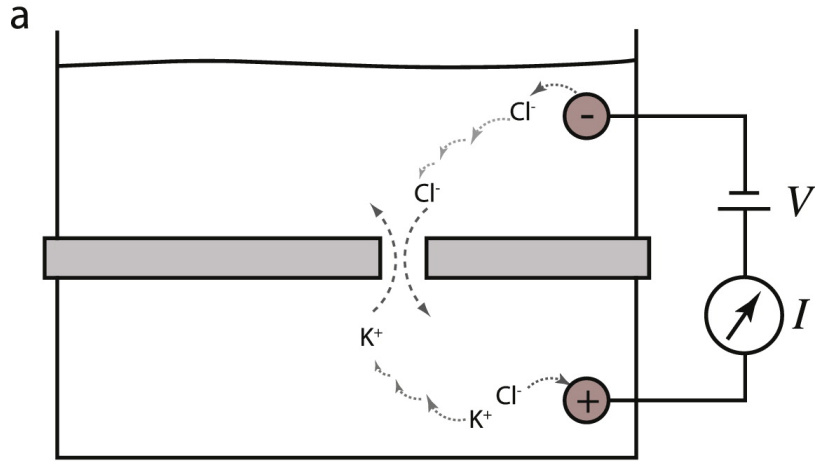


DNA, RNA, protein sequencing

Filtration



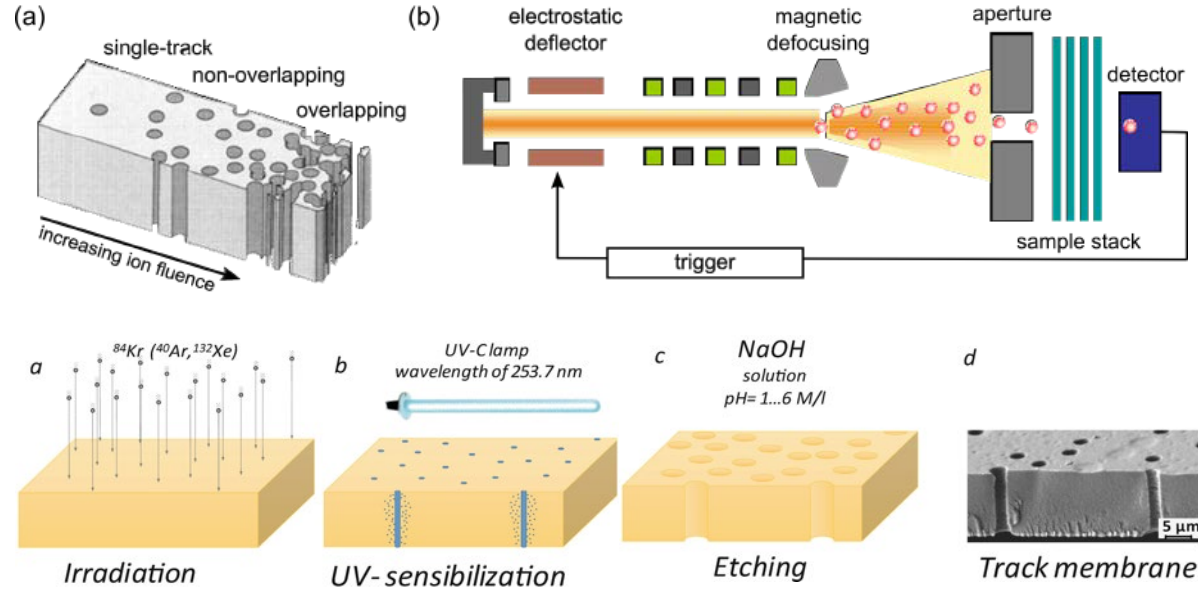
Osmotic power generation



Wanunu, M. (2012). Nanopores: A journey towards DNA sequencing. Physics of Life Reviews, 9(2), 125–158.

Solid-State Nanopore Technology

Polymer & Silicon Nitride platforms

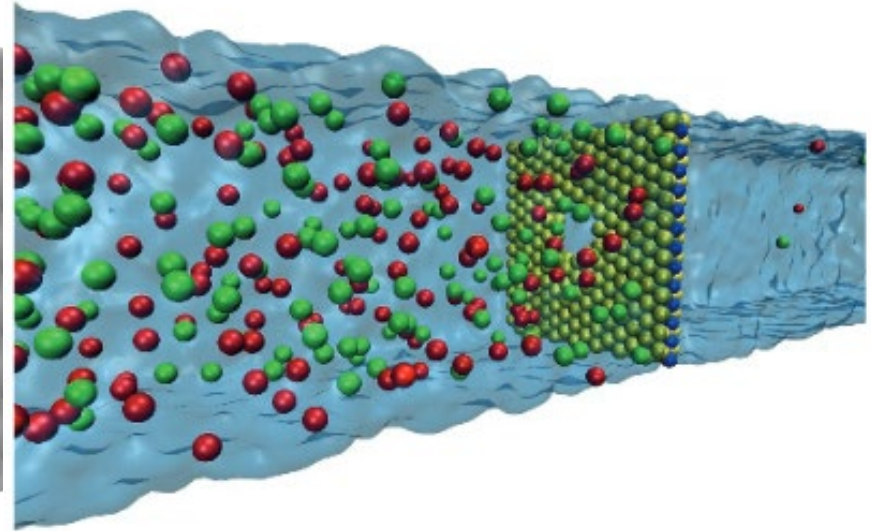
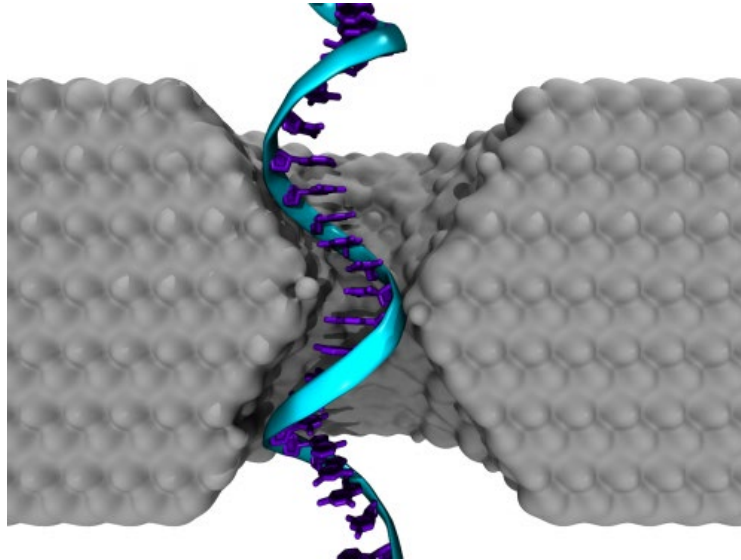


Commercialized Fabrication Technology

Available to various materials & Accessible for different nano-geometry

Solid-State Nanopore Technology

Polymer & **Silicon Nitride Platform** (Relatives: Dielectric, 2D Materials, ...)

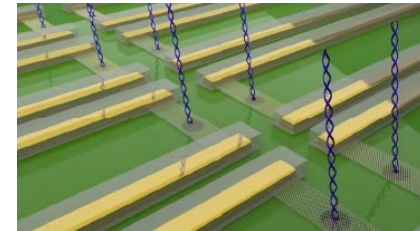
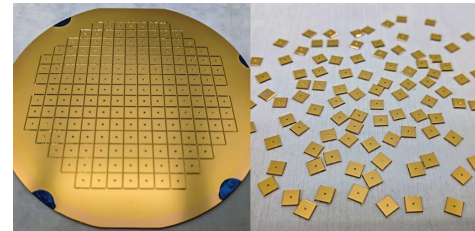
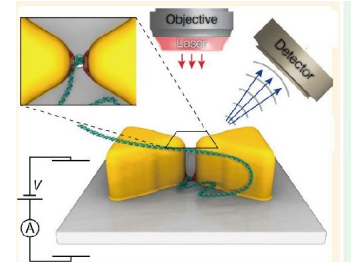
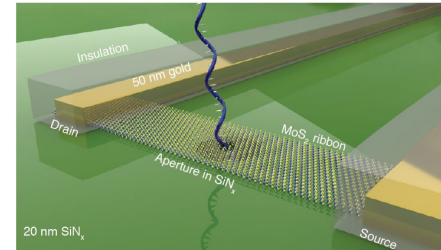
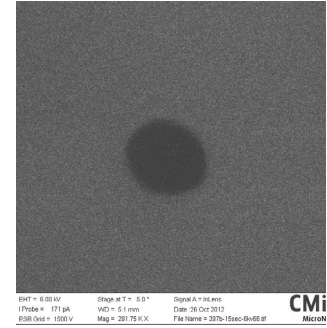
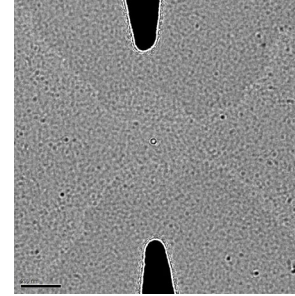
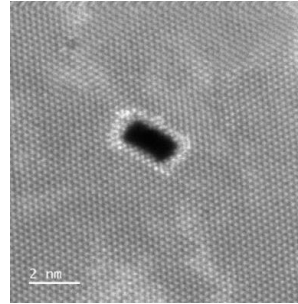


<https://phys.org/news/2013-05-advance-nanotech-gene-sequencing-technique.html>

Feng, J. et al. Single-layer MoS2 nanopores as nano power generators. Nature 536, 197–200 (2016).

EPFL Solid-State Nanopores

- Different materials
- Integration with electrical sensing
- Integration with optical sensing
- High-throughput production



Graf,Radenovic *Nano Letters* 2019.



Bioinspired Solid State Nanopores

Background Information

Clean Room Technology

Applications

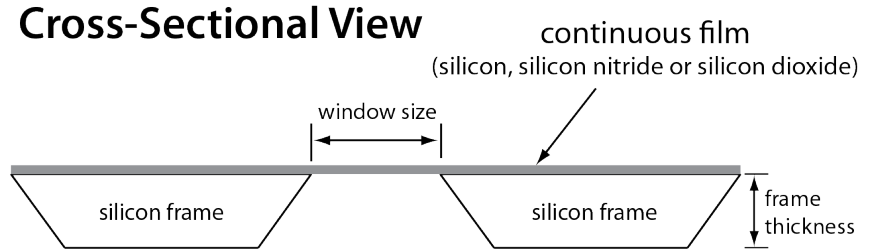
Further Plan

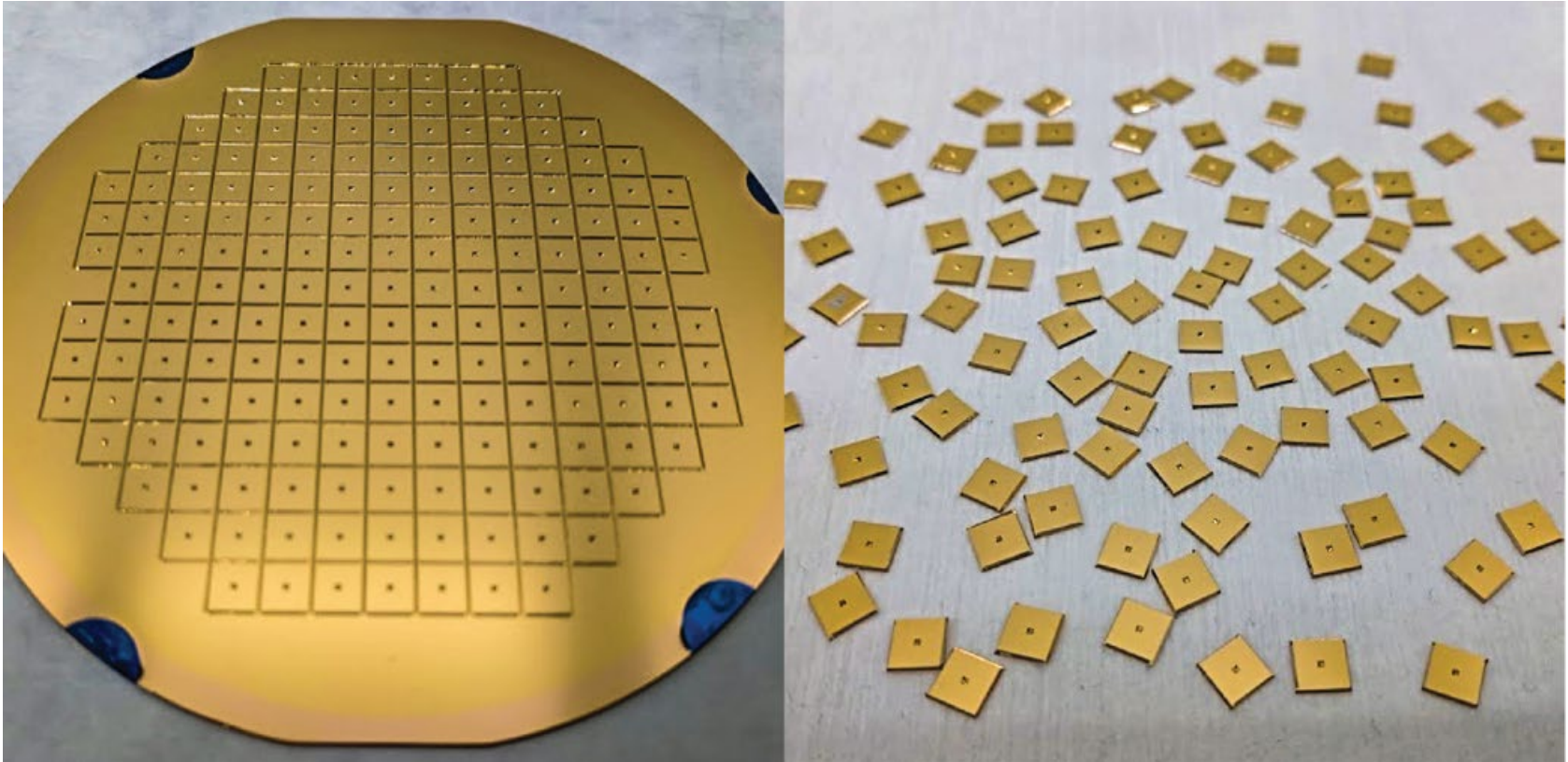
Acknowledgement

From TEM Sample Grid to Universal Research Platform

Silicon Nitride freestanding membrane is designed for TEM window grid. **(Silicon Oxide)**

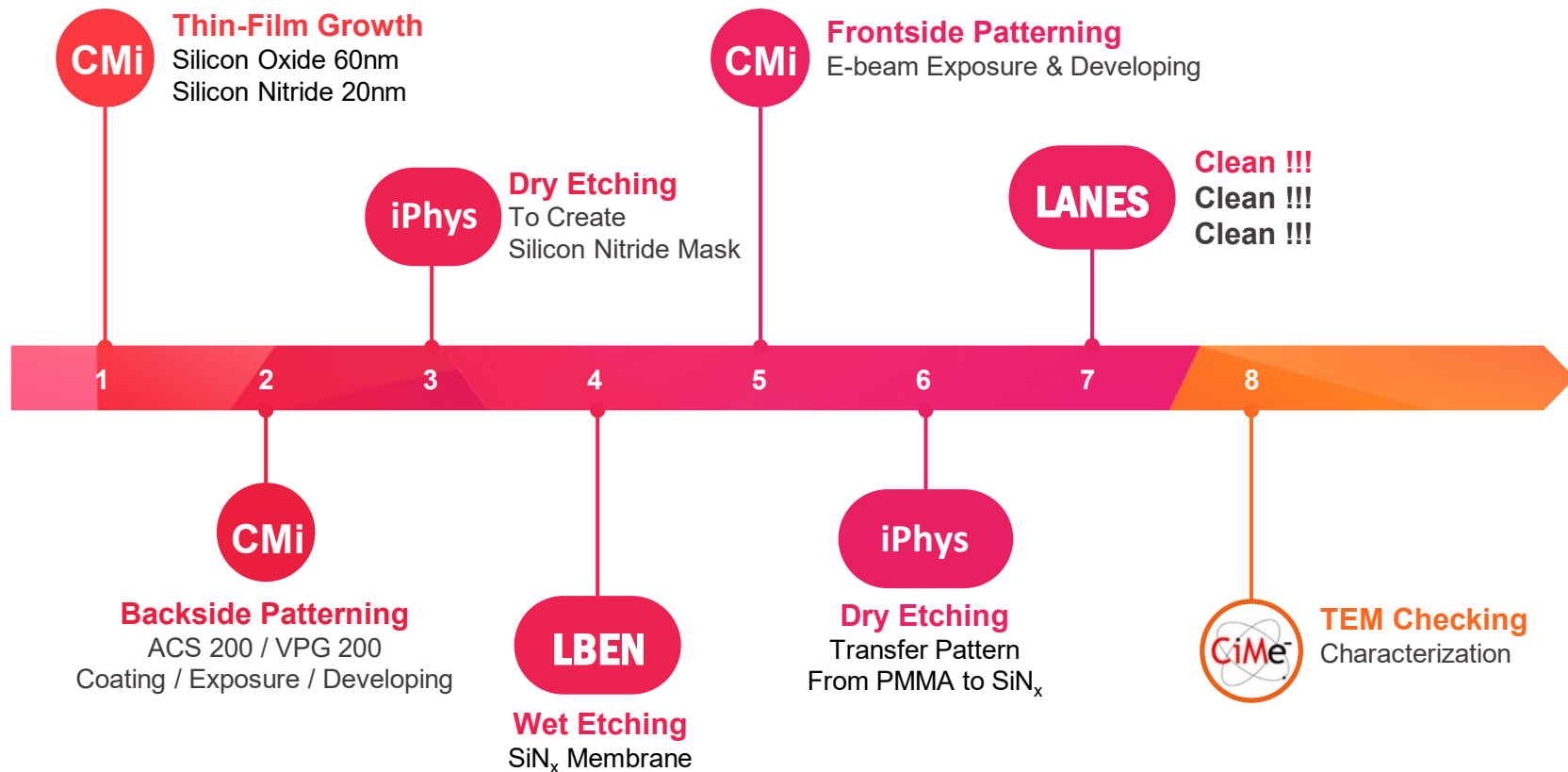
- **Simple Substance Composition.**
- **High Surface Flatness.**
- **High Chemical Tolerance.**
- **High Electronic Transparency.**
- **Cleanness**
- **Controllable Structure**
- **Stability**
- **Thickness**





4-Inches Wafer-Scale Fabrication

Mask-Free Procedure



How do we get our SiN_x substrate platforms?

(a)

Film deposition
(i) Dry thermal SiO_2
(ii) LPCVD LS SiN_x



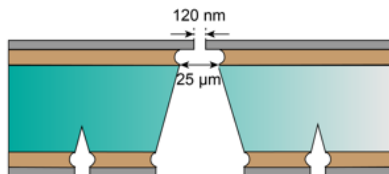
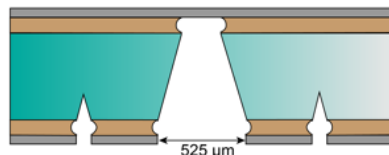
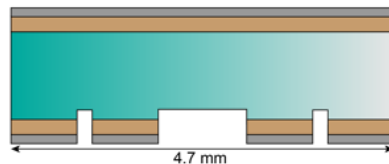
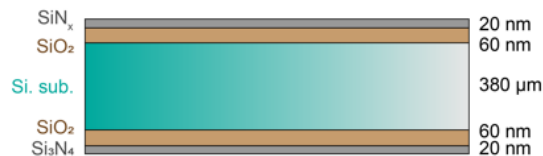
Back-side photolithography/RIE
(i) Direct-laser writer patterning
(ii) $\text{SiN}_x/\text{SiO}_2$ dry etch



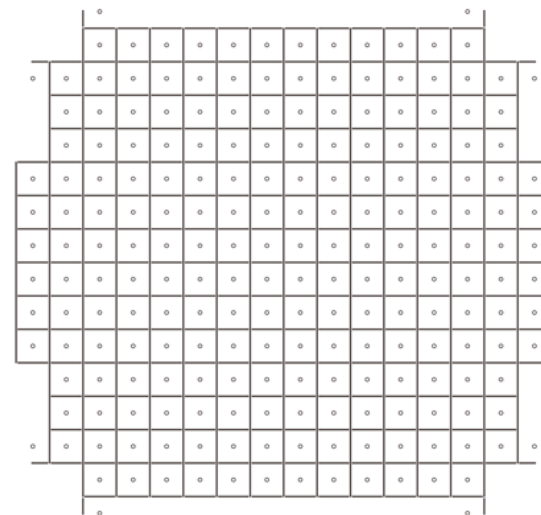
Wet etching
(i) Si/SiO_2 substrate etching with KOH



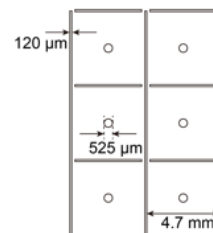
Front-side EBL/RIE
(i) Nanopore EBL patterning
(ii) $\text{SiN}_x/\text{SiO}_2$ dry etch



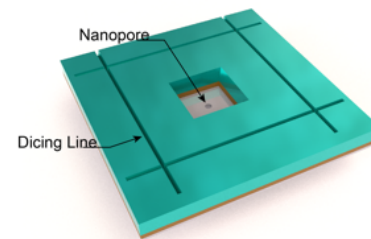
(b)



(c)

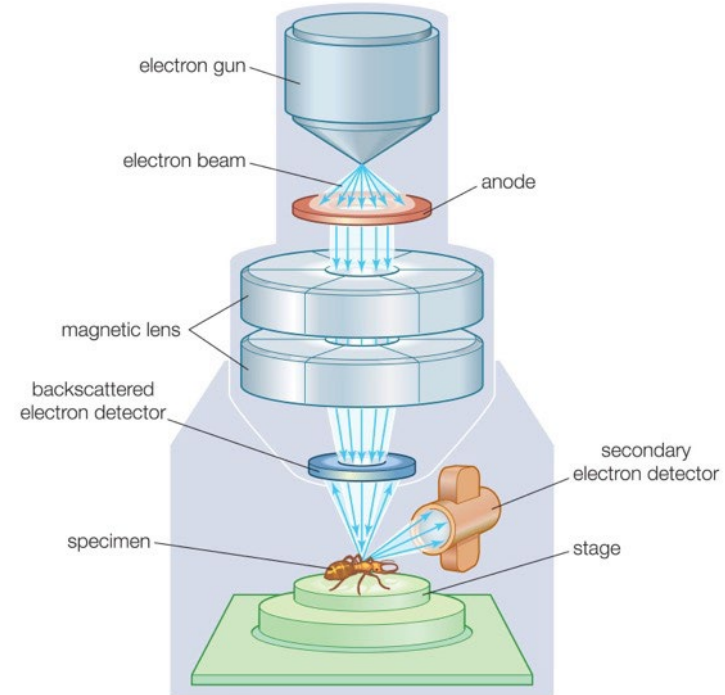
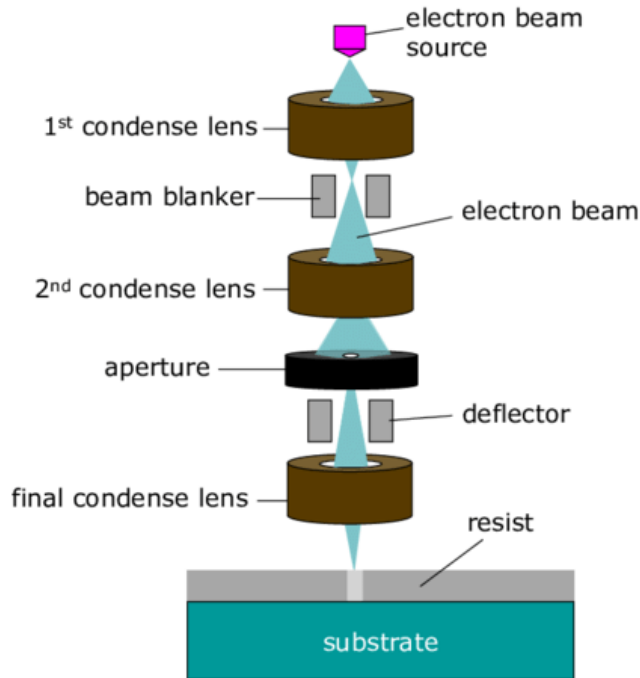


(d)



Advantage of E-beam Lithography

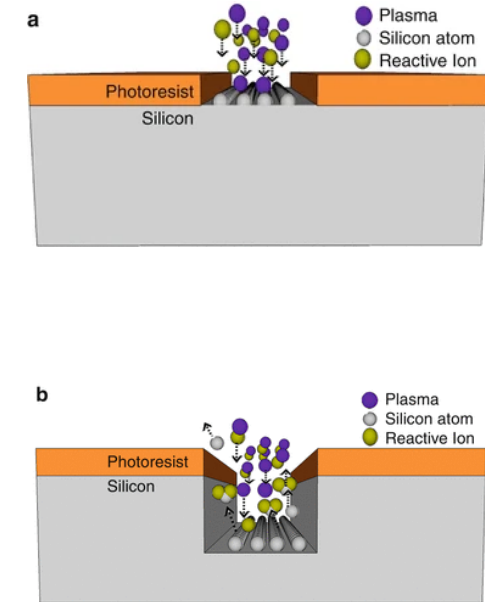
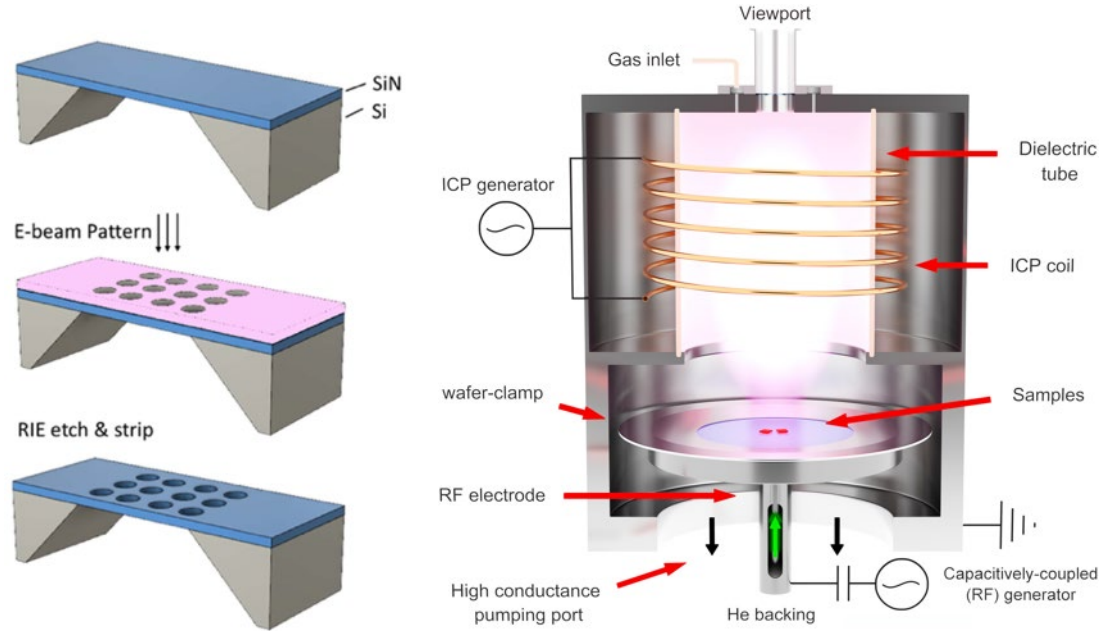
Direct Writing Technology



© 2012 Encyclopædia Britannica, Inc.

- **Electron Beam Lithography** is similar as **Scanning Electronic Microscopy**
- **Deflector** of E-beam Lithography: Direct Writing Realizing Customizing Design

Reactive Ion Etching (RIE) – Fabricate Pores



- **Reactive ion etching (RIE)** is a plasma process where radiofrequency (RF) discharge-excited species (radicals, ions) etch substrate or thin films in a low-pressure chamber.
- **High Selectivity & High Anisotropy & High Etching Rate**

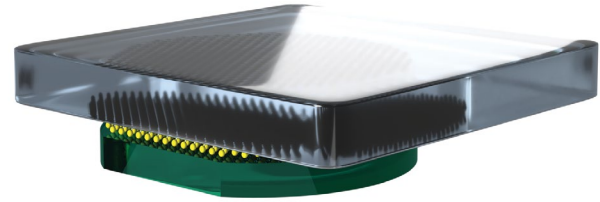
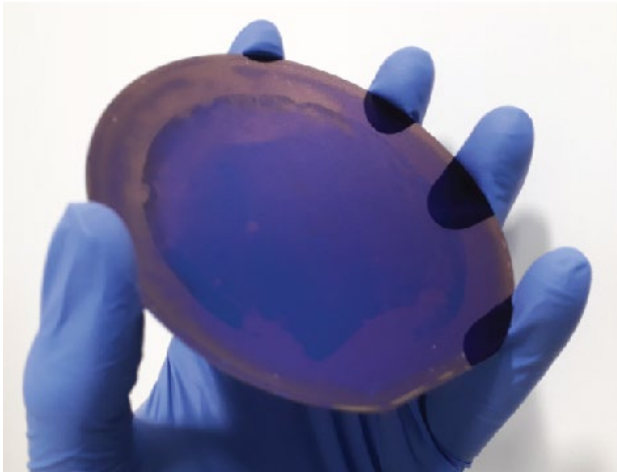
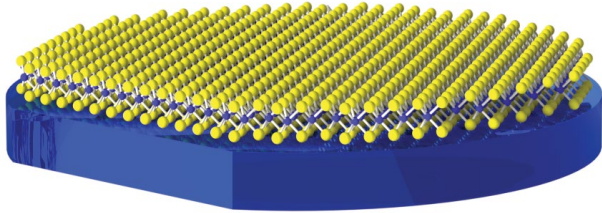
Verschueren, D. V., Yang, W. & Dekker, C. Lithography-based fabrication of nanopore arrays in freestanding SiN and graphene membranes. *Nanotechnology* 29, 145302 (2018).

Godin, B. et al. Encyclopedia of Nanotechnology. 587–589 (2012).

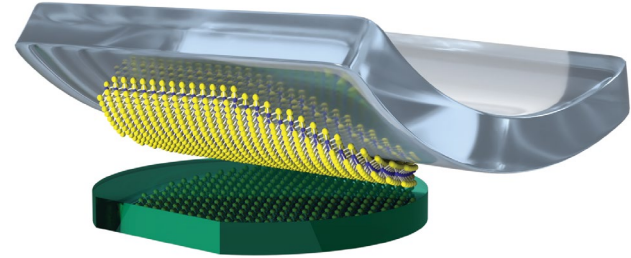
Hönl, S., Hahn, H., Baumgartner, Y., Czornomaz, L. & Seidler, P. Highly selective dry etching of GaP in the presence of Al_xGa_{1-x}P with a SiCl₄/SF₆ plasma. *J Phys D Appl Phys* 51, 185203 (2018).

EPFL Wafer scale transfer

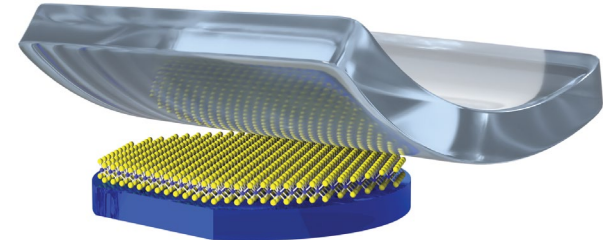
Complete dry-transfer of MoS_2 on SiNx wafer
(nanopore devices)



PDMS/ MoS_2 on sapphire substrate

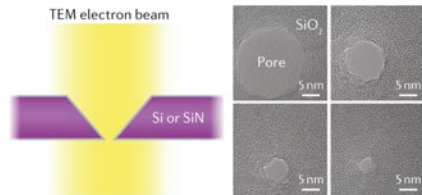


Water-assisted lift-off process

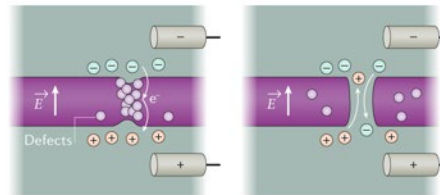


Different Materials & Fabrication Strategy

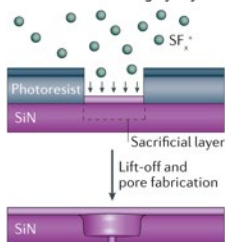
a Pore formation by focused electron/ion-beam milling



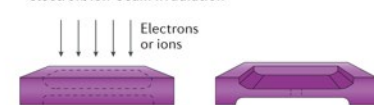
b Pore formation by controlled dielectric breakdown



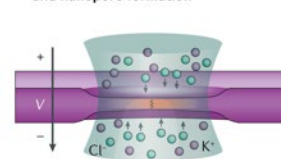
c Membrane thinning by dry etching



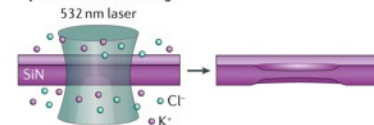
d Membrane thinning by electron/ion-beam irradiation



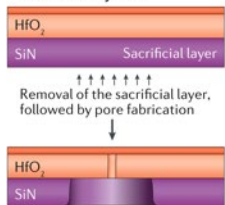
f Simultaneous membrane thinning and nanopore formation



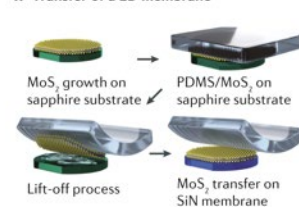
e Membrane thinning by laser-assisted photothermal etching



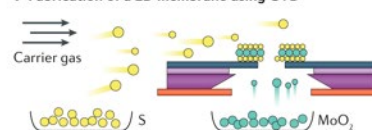
g Pore formation in a thin membrane fabricated by ALD



h Transfer of a 2D membrane



i Fabrication of a 2D membrane using CVD

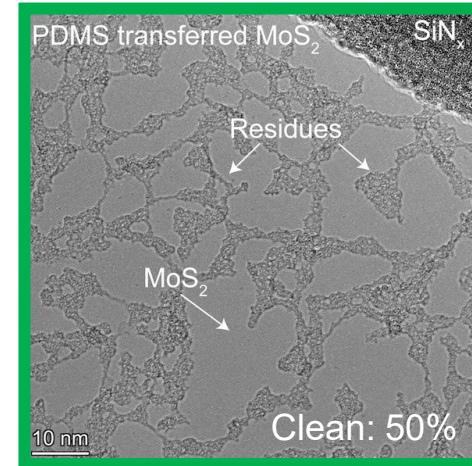
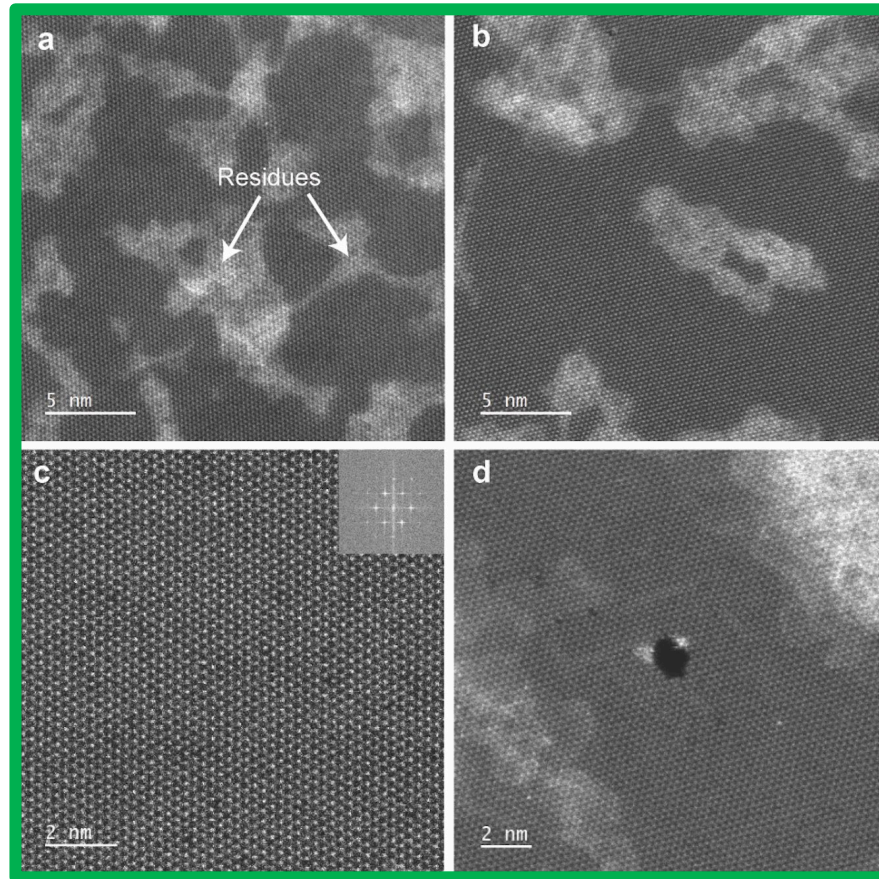


Fabrication Strategy

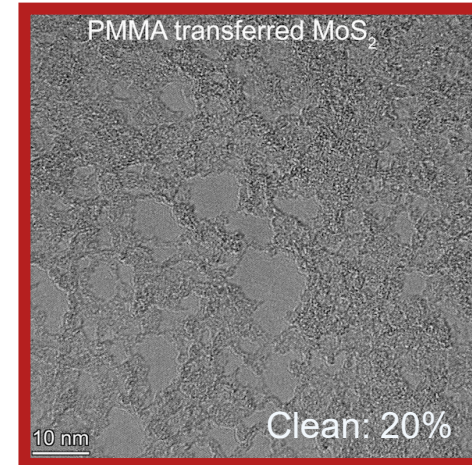
- **TEM Drilling**
- **Dielectric Breakdown**
- **Dry Etching**
- **Photothermal Etching**
- **Drilling on ALD-additional Layer**
- **Transferred MoS2 Nanopore**
- **CVD MoS2 Nanopore**

Materials

- **Silicon Nitride**
- **HfO2 (Dielectric materials)**
- **2D Materials (MoS2 Graphene ...)**

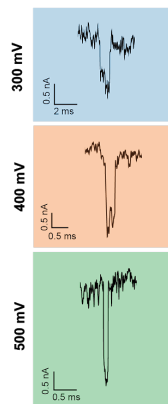
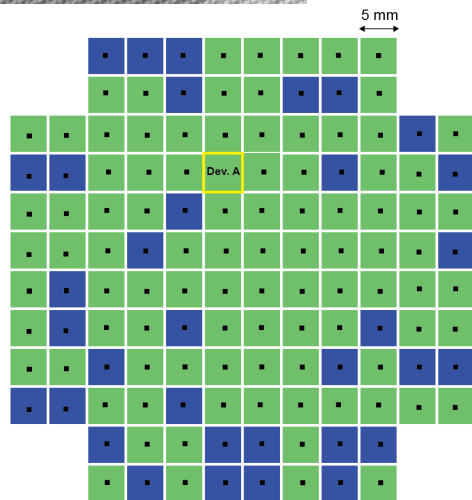
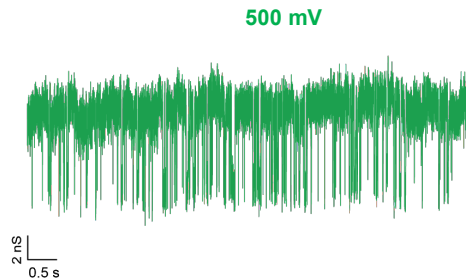
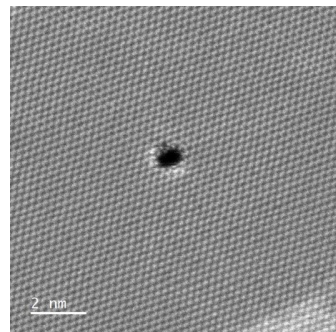


PDMS

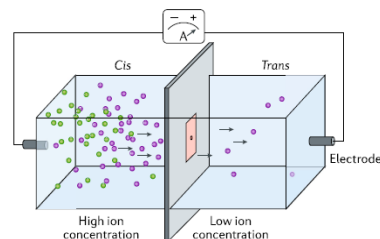


PMMA

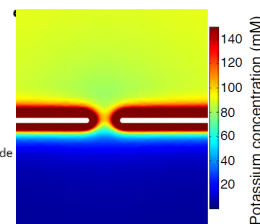
Nanopore devices benchmarking



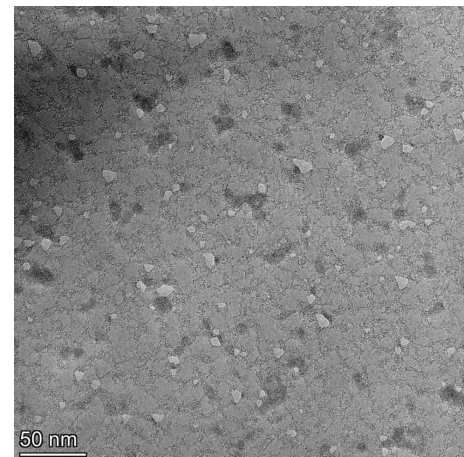
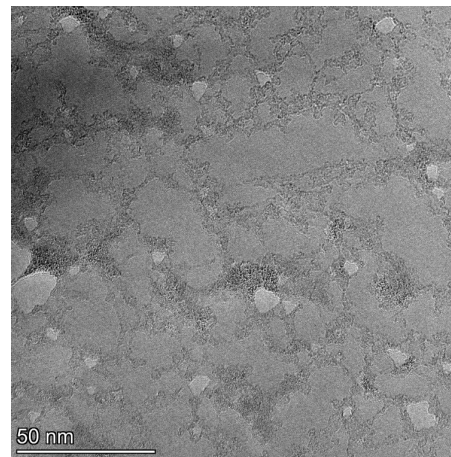
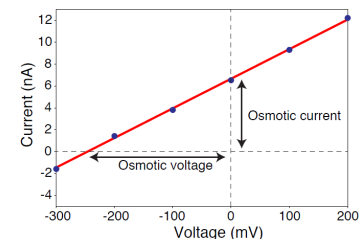
concentration gradient + ion selectivity =



Potassium selective



net current



Feng ...Radenovic *Nature* **2016**.

Macha, Marion... Radenovic *Nature Rev. Materials* **2019**.

Macha, Marion... Radenovic *ACS Nano* **2023**.

Disadvantage of Silicon Nitride

Limited Surface Properties & Relatively Poor Stability

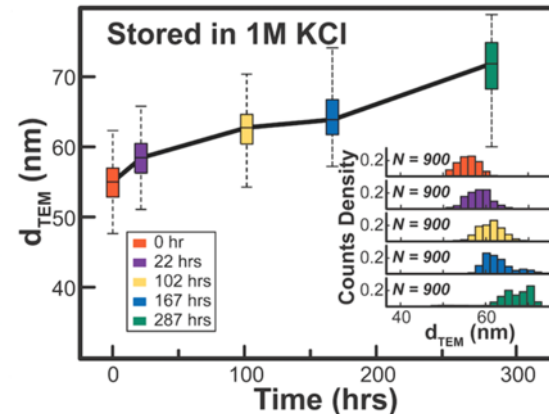
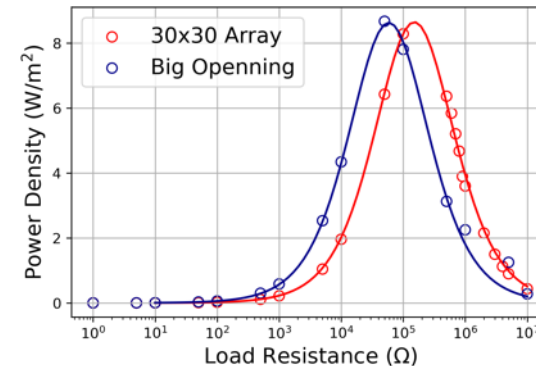
Limited Surface Properties

- Limited Surface Charge
- Limited Output in Osmotic Energy Harvesting

Limited Stability

- Nanopore Enlargement due to the Dissolving
- Lower Stability in electrolyte solution
- In Industrial Application Scenarios Require

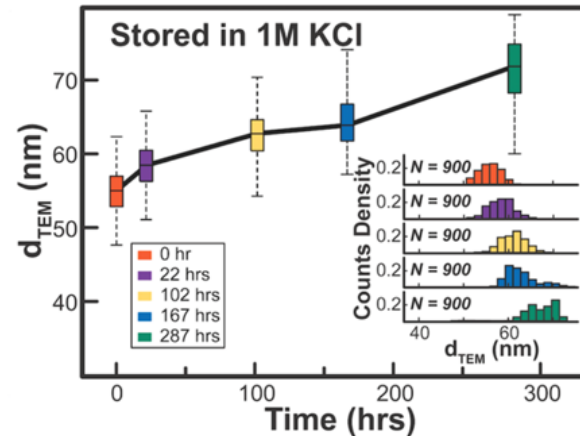
Working for Months !



Stability

Limited Stability

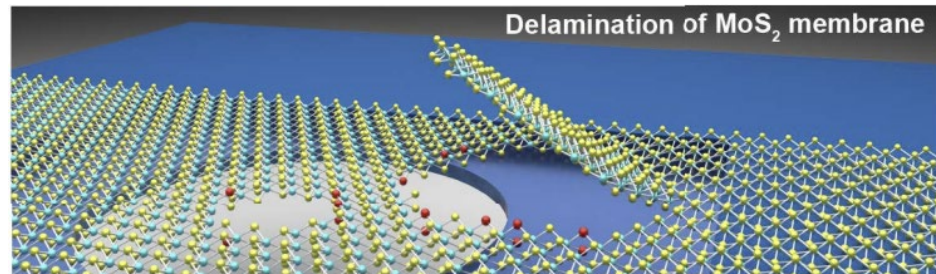
- Nanopore Enlargement due to the Dissolving
- Lower Stability in an electrolyte solution
- Industrial Applications Require long-term stability



Chou,., Das,..... & Drndić, M. *Acs Nano* **2020**.

Working for Months!

- Reinforcing adherence of 2D material to the substrate of the silicon nitride platform



Thakur, Cai,... Radenovic *npj 2D Mater Appl* **2023**

Thin-film Technology

How to Improve SiNx Nanopore with **Microfabrication Compatible** Process.

Thin-film Technology

- Introducing thin layer of specific materials
- Usage
 - Changing Surface Property
 - Providing / Avoiding Electric Conducting
- Deposition Method
 - **Chemical Deposition**
 - Physical Deposition



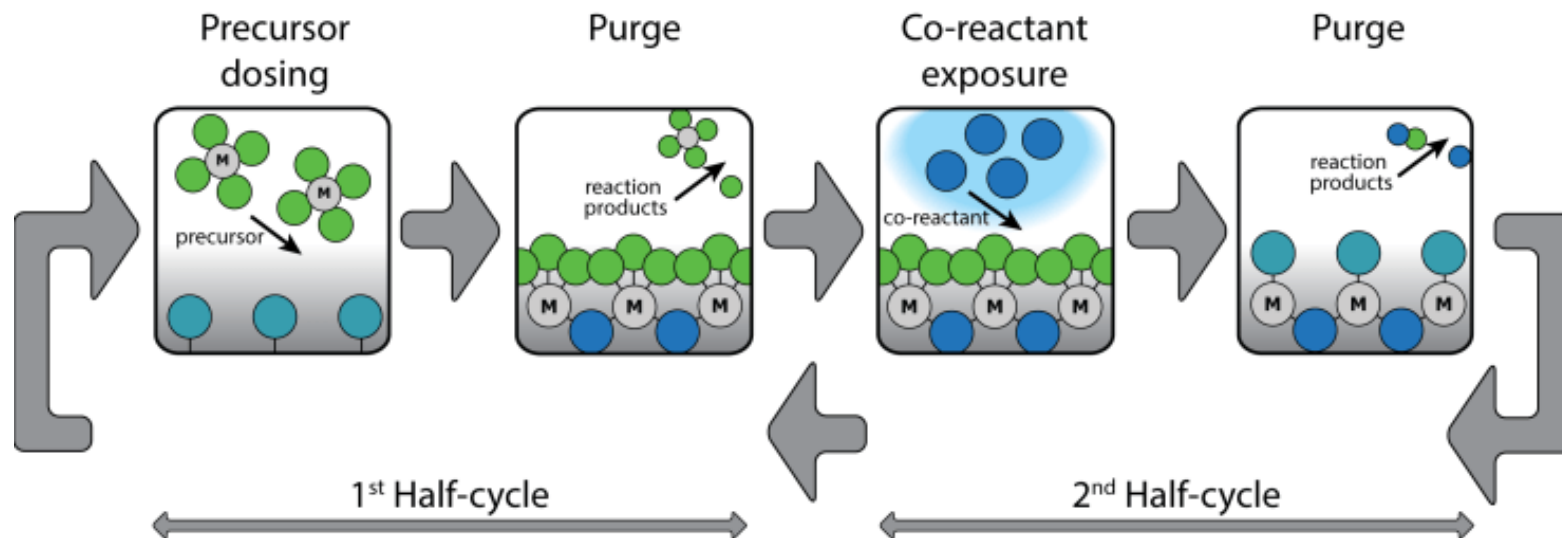
CVD
Chemical Vapor Deposition



ALD
Atomic Layer Deposition

How ALD Work?

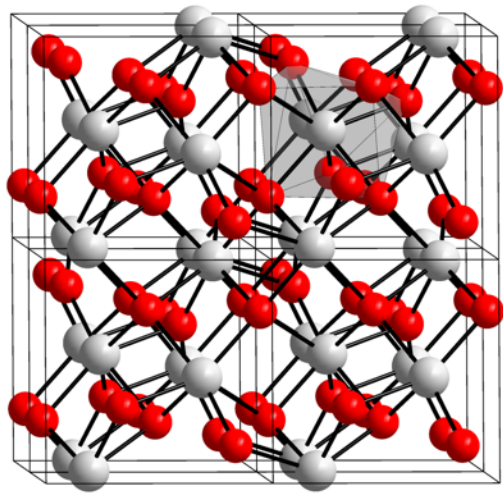
Atomic Layer Deposition



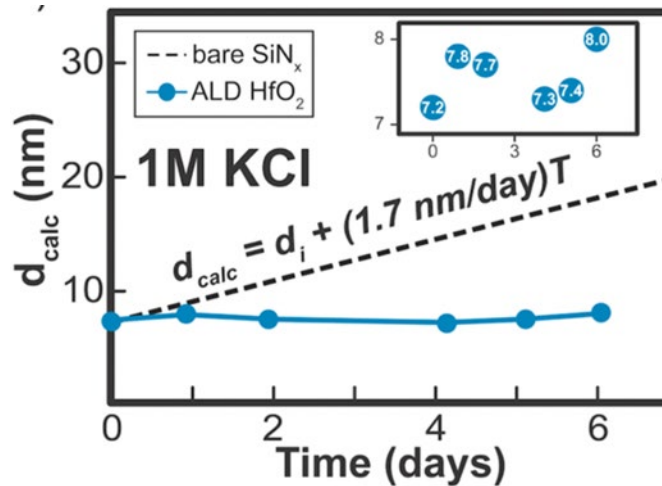
- **Atomic layer deposition (ALD)** is a thin-film deposition technique based on the sequential use of a gas-phase chemical process; it is a subclass of chemical vapor deposition (**CVD**).
- **Uniformity & Self-Limiting**

Hafnium(IV) oxide Functionalized Nanopore

High Stability Materials



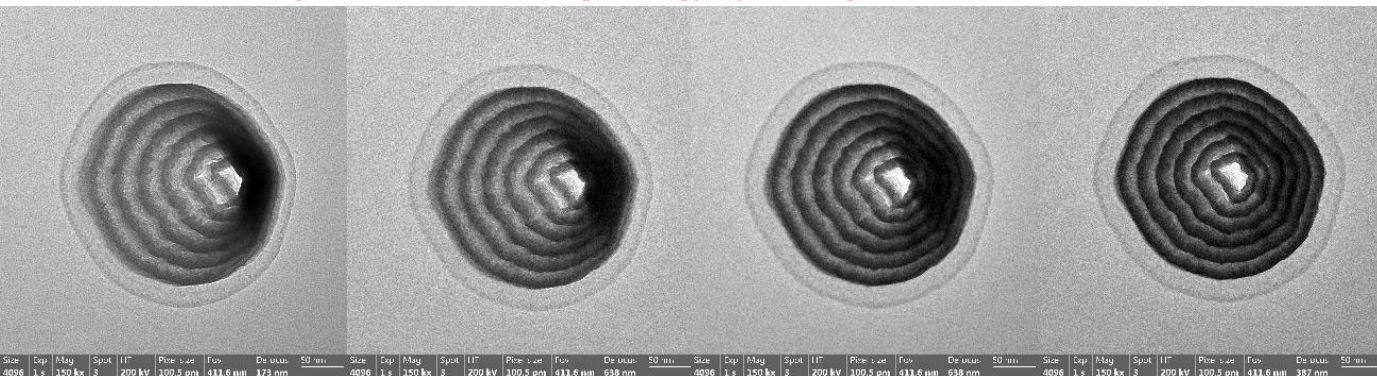
- **Hafnium(IV) oxide**
- Introduced by **Intel** for gate insulator in field-effect transistors
- The dielectric constant of HfO_2 is **4–6 times higher** than that of SiO_2



- **Nanopore Application [Present Research]**
 - HfO_2 functionalized Nanopore (ALD)
 - Stability in Room Temperature KCl Solution **[6 Days]**
 - Stability in 60°C KCl Solution under 532nm Laser Irradiation **[10 mins]**

HAADF STEM imaging

Insight on the 3D Morphology by Tilting



-20

-15

-10

-5

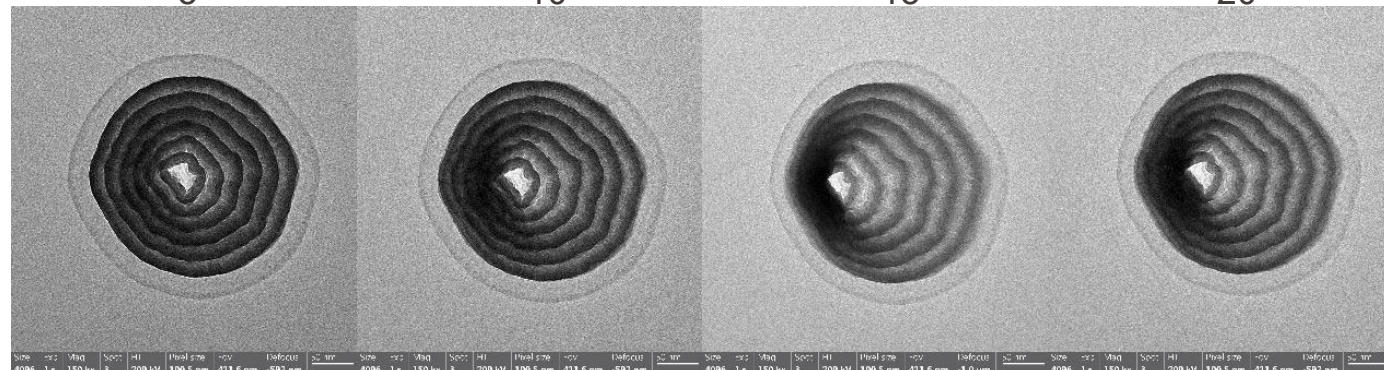
Tilt angles

5

10

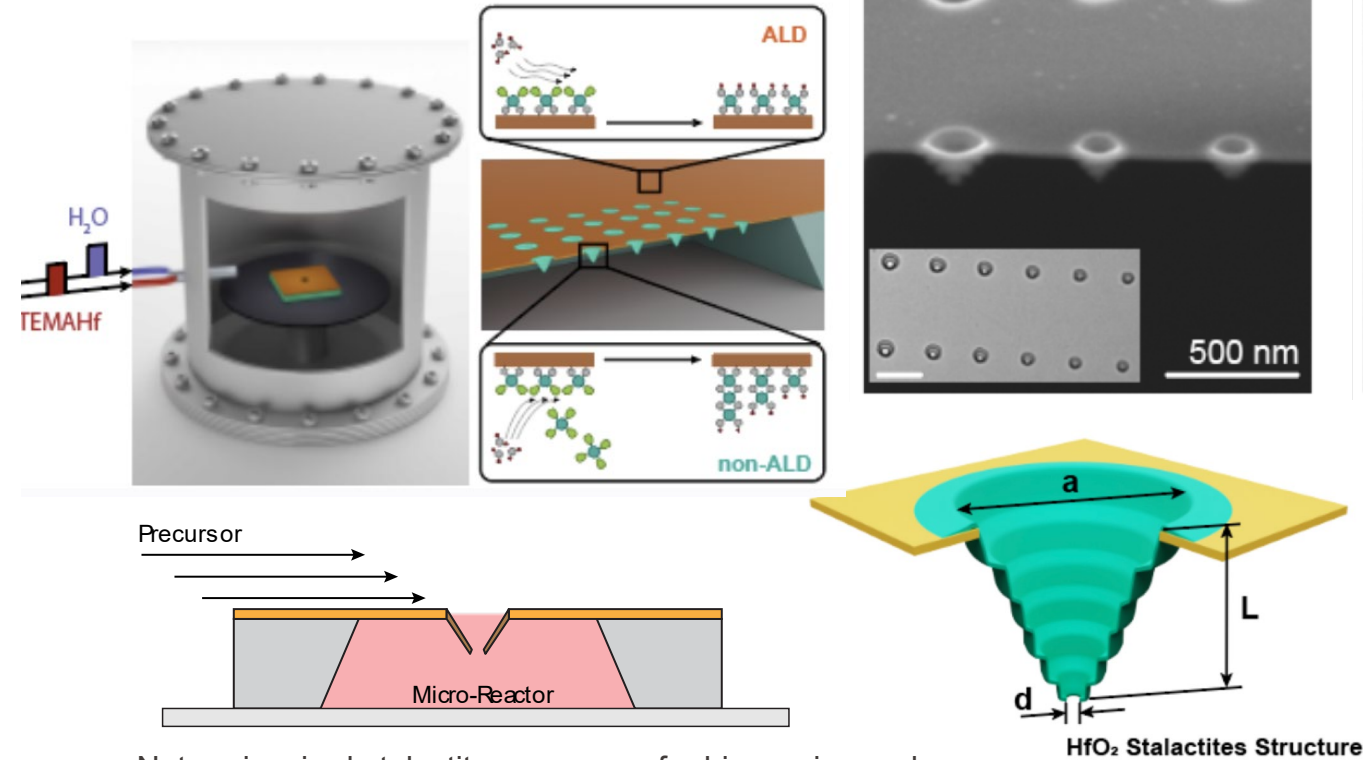
15

20



Thin-film Technology for Silicon Nitride Aperture Functionalization

Atomic Layer Deposition (H_2O + TEMA-Hf)



Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

■ PCT 23 170 779.5

HfO₂ Stalactite-like Nano-Structure

Elemental analysis with STEM

■ Cross-section

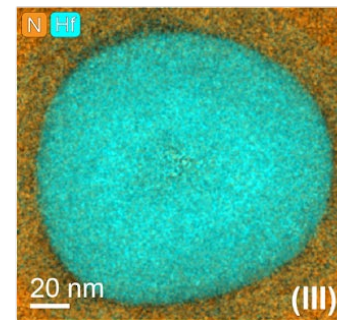
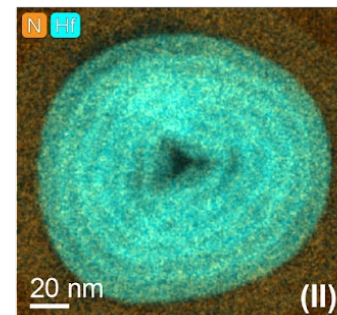
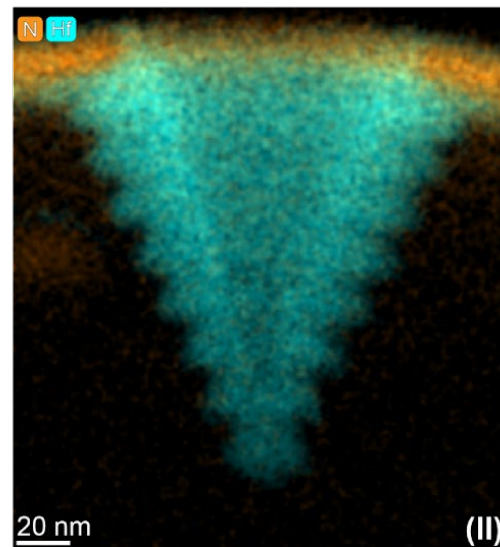
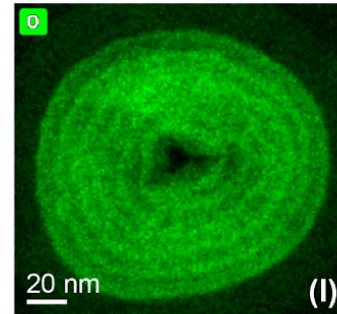
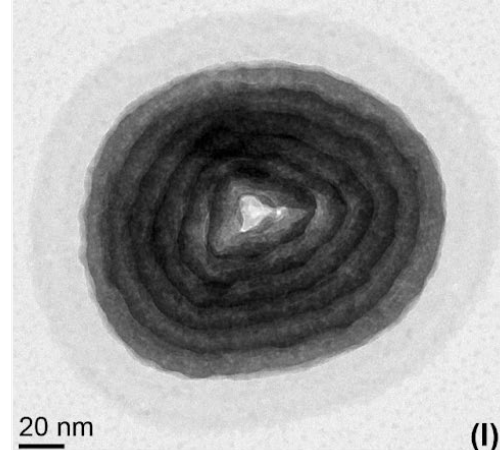
- Localization Hf and N
- Corresponding to HfO₂ and Silicon Nitride

■ Composition recognition

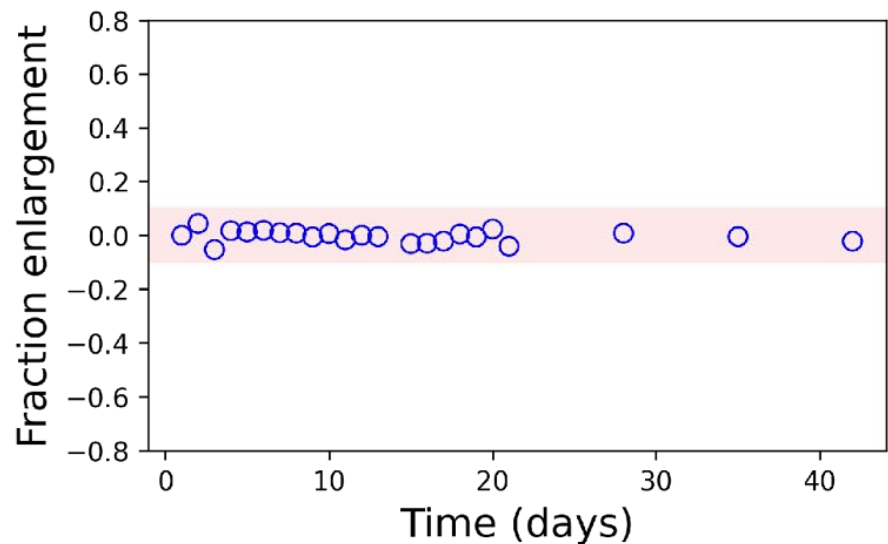
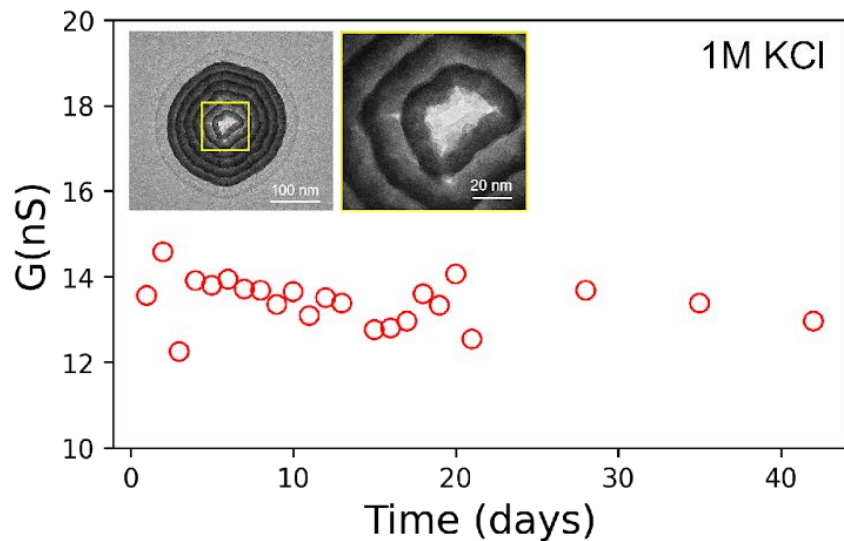
- HfO₂
- Silicon Nitride
- Homogenous distribution inside HfO₂ nanostructure.

Nature-inspired stalactite nanopores for biosensing and energyharvesting Chernev *, Teng*,Radenovic*
Advanced Materials **2023**

PCT 23 170 779.5



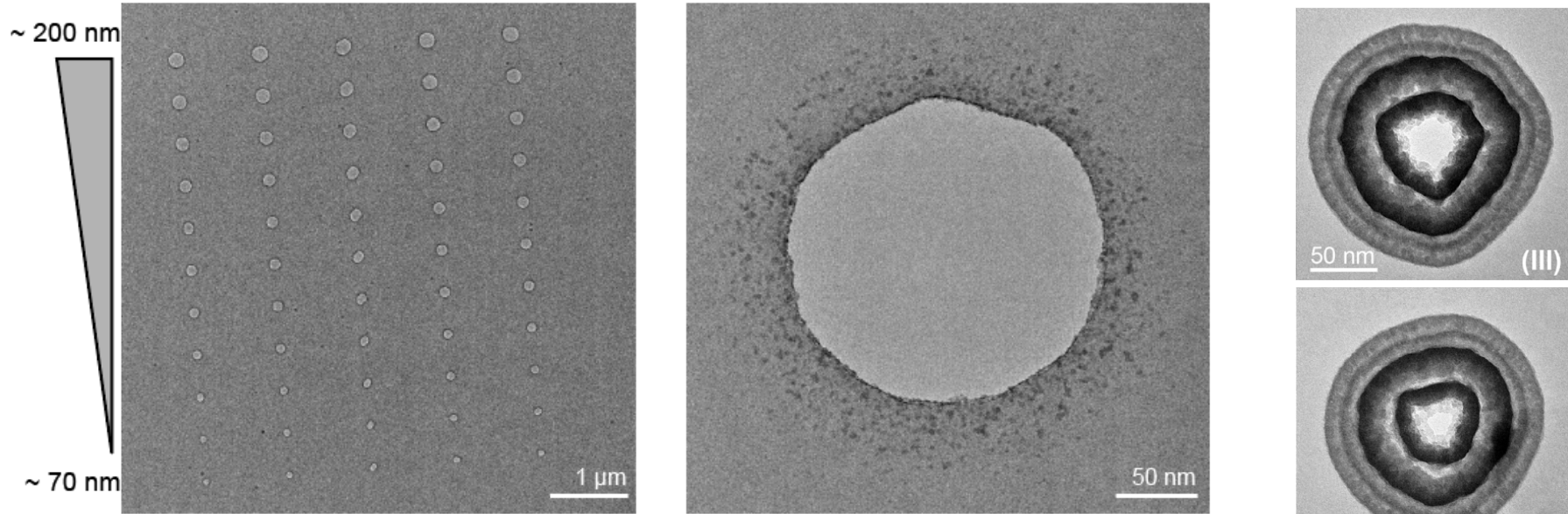
- Conductance of 1M KCl electrolyte solution in **42 days**
- Variation with in 10%



Nature-inspired stalactite nanopores for biosensing and energy

harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

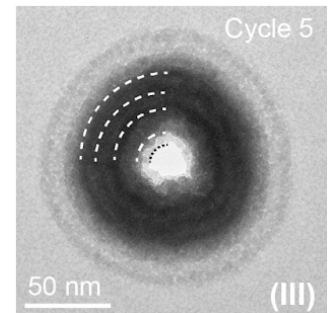
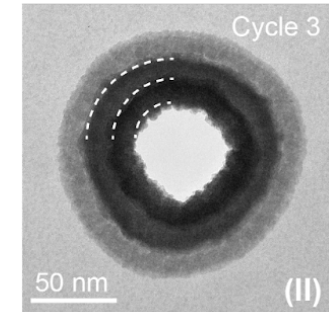
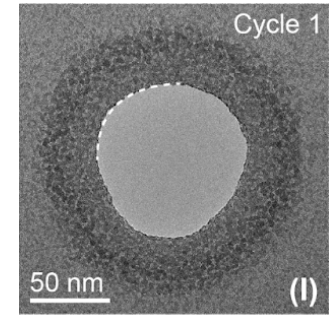
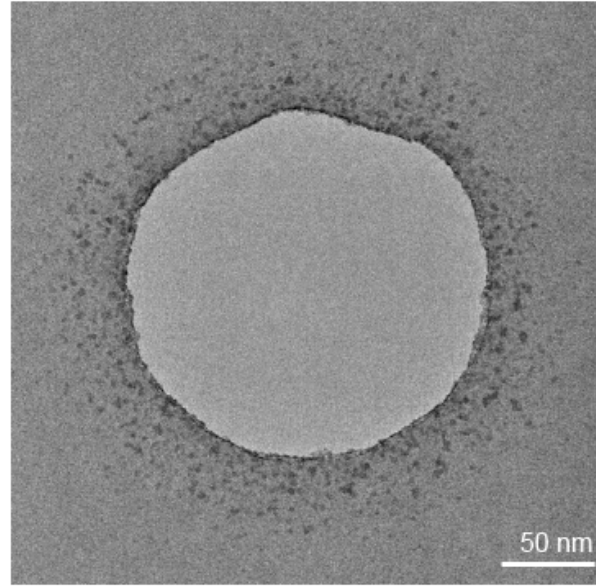
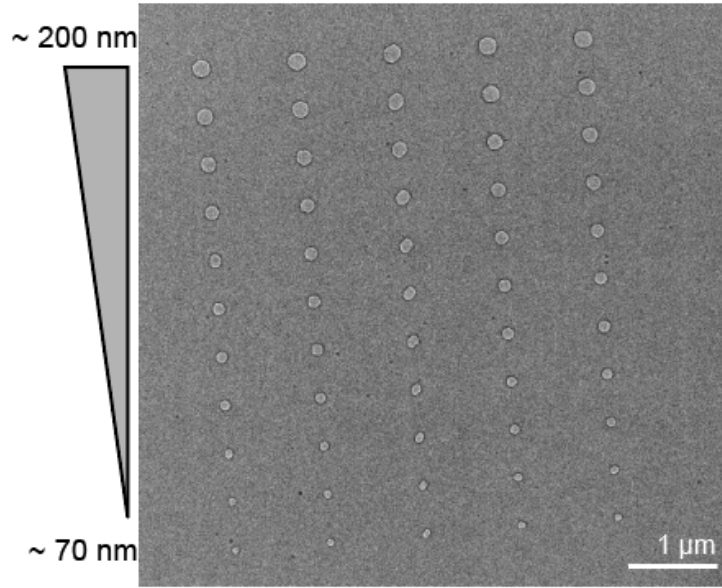
- PCT 23 170 779.5



- The number of steps in HfO₂ Nanostructure (n) => Steps of the growth process (n+1)
- Critical Parameter in Nanostructure (Diameter)=> Different Starting Diameter of Aperture
- Whether Starting the non-ALD Growth Process=> Different Purging Time

Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

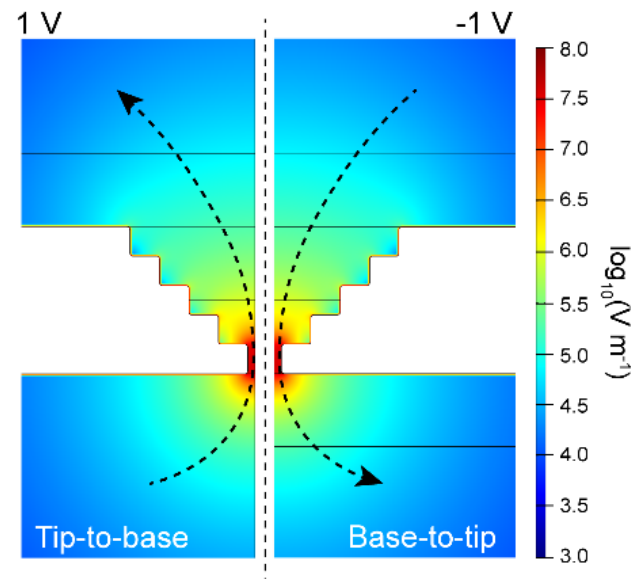
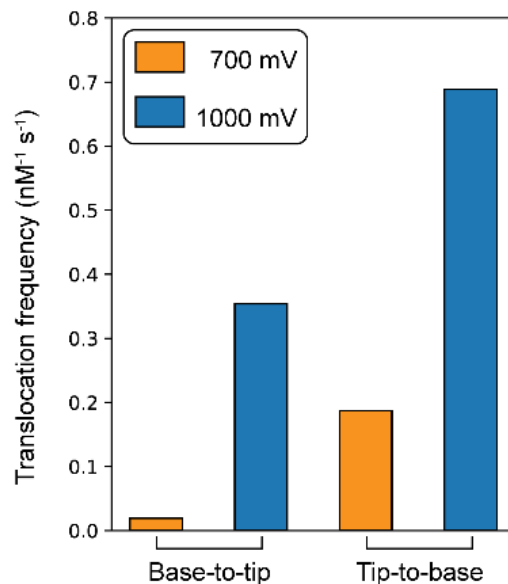
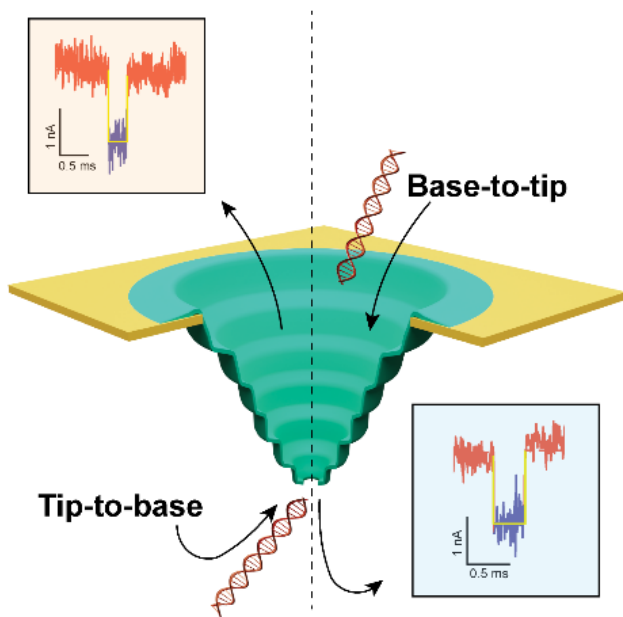
- PCT 23 170 779.5



- The number of steps in HfO_2 Nanostructure (n) \Rightarrow Steps of the growth process ($n+1$)
- Critical Parameter in Nanostructure (Diameter) \Rightarrow Different Starting Diameter of Aperture
- Whether Starting the non-ALD Growth Process \Rightarrow Different Purging Time

Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

- PCT 23 170 779.5

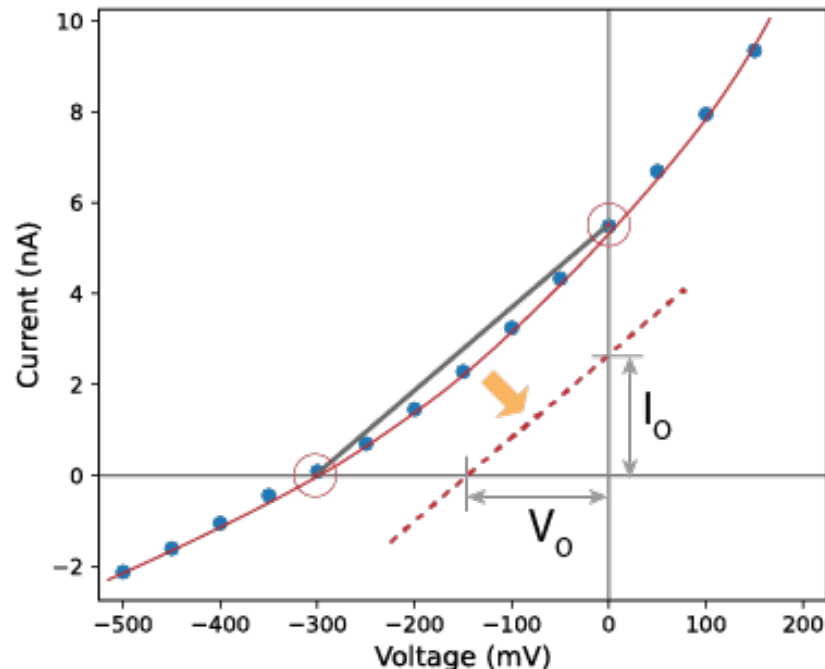
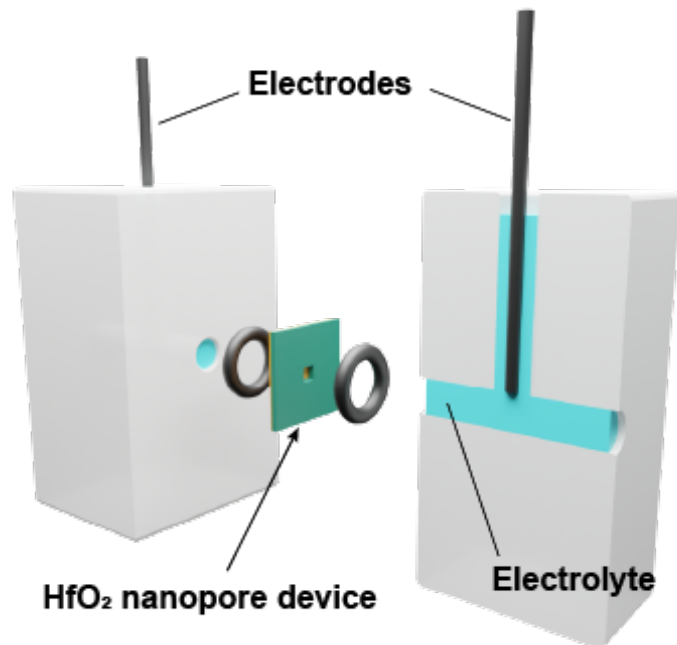


- Geometry Defines Two Direction: **Tip-to-base** / **Base-to-tip**.
- Translocation events : **Tip-to-base** is always more than **Base-to-tip**.

Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

Osmotic Energy Conversion – Single Nanopore Devices

Set up and Basic Characteristics



$$\varepsilon_{\text{osm}} = \frac{k_B T}{ze} S \ln \frac{c_h}{c_l}$$

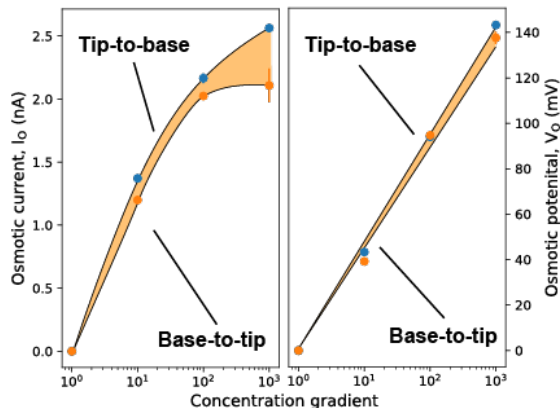
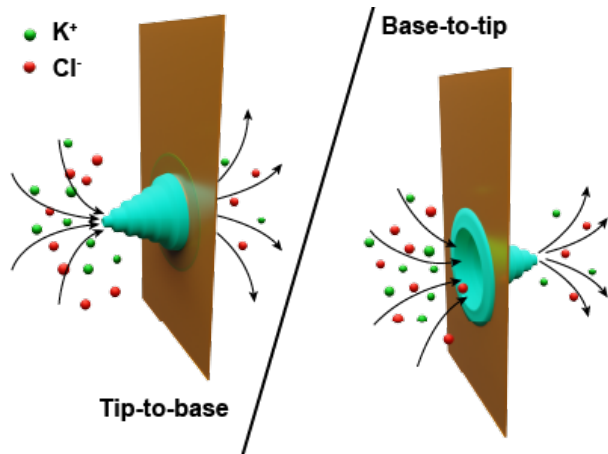
S: Ionic Selectivity

Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

■ PCT 23 170 779.5

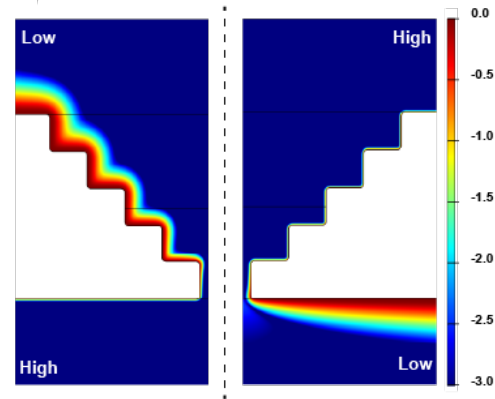
Osmotic Energy Conversion – Single Nanopore Devices

Asymmetric Diffusion from Asymmetric Geometry



Relative Distribution

log(Local distribution bias)



$$\text{Local distribution bias} = \frac{|c_{K^+} - c_{Cl^-}|}{c_{K^+} + c_{Cl^-}}$$

- Geometry Defines Two Direction: **Tip-to-base** / **Base-to-tip**.
- Osmotic Conversion Efficiency: **Tip-to-base** is always higher than **Base-to-tip**.
- Finite Element Simulation : Localized Relative Ions Distribution Difference

Electric Double Layer expanded inside the nanochannel provide more selectivity (Left)

Nature-inspired stalactite nanopores for biosensing and energy

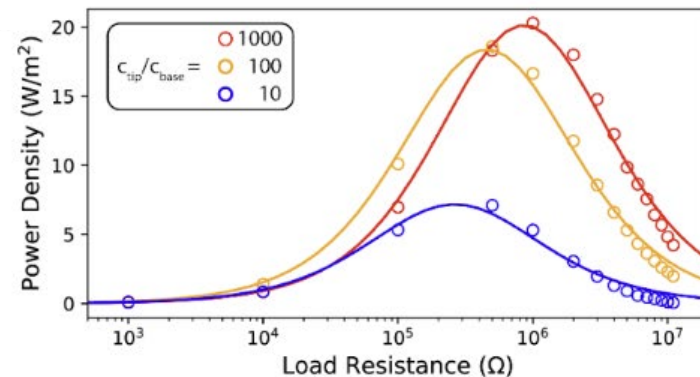
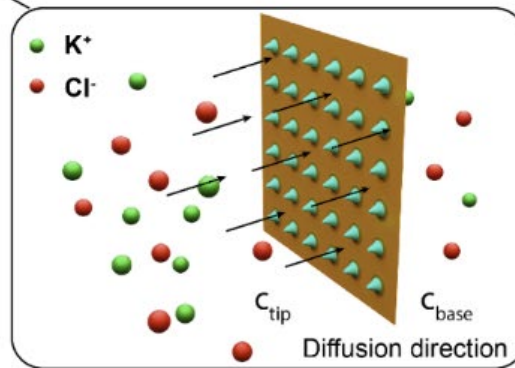
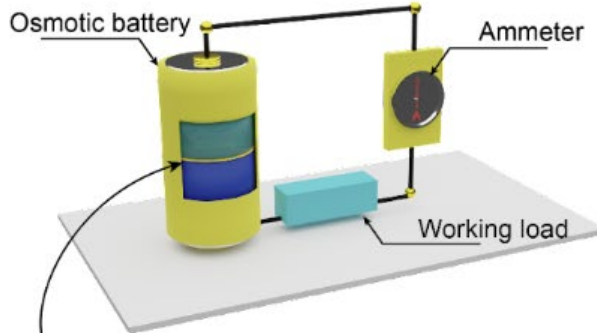
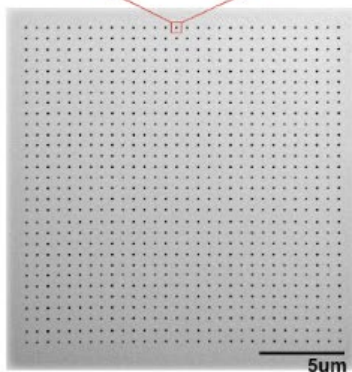
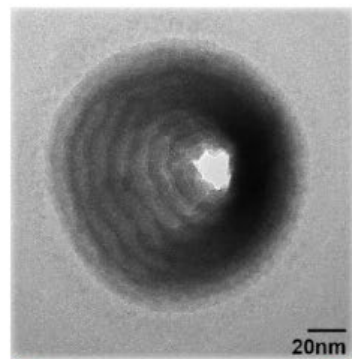
harvesting Chernev *, Teng*,Radenovic* Advanced Materials 2023

- PCT 23 170 779.5

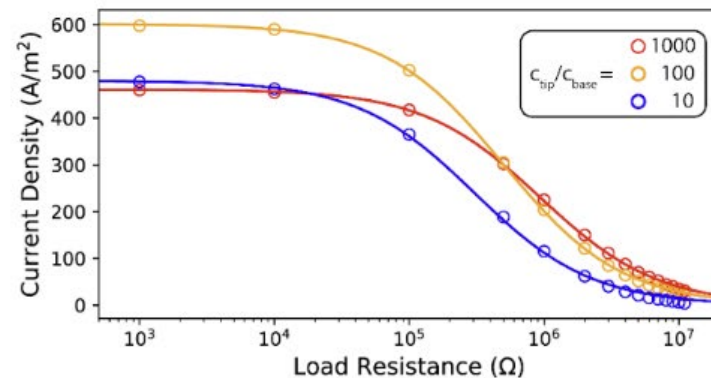
Our Result: ~0.35 nW / pore

| MoS₂: ~1 nW / pore

| hBN Nanotube: ~0.02 nW / Tube



(d)



Nature-inspired stalactite nanopores for biosensing and energy harvesting Chernev *, Teng*,Radenovic* Advanced Materials **2023**

Conclusion

New adaptable platform in terms of geometry and material composition – with inherent scalability, stability

Applications

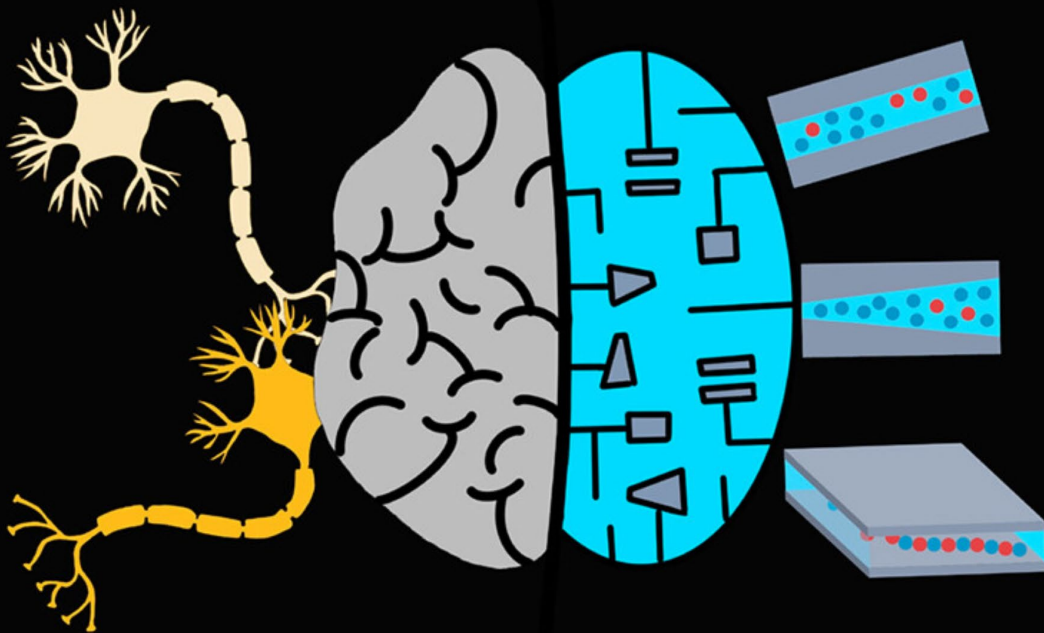
- basic nanofluidics research**
- biosensing -multi-omics**
- ionotronics**
- energy harvesting**
- filtration**

Learning from the Brain: Bioinspired Nanofluidics

39

iker

Brain-inspired nanofluidic iontronics



Advantages

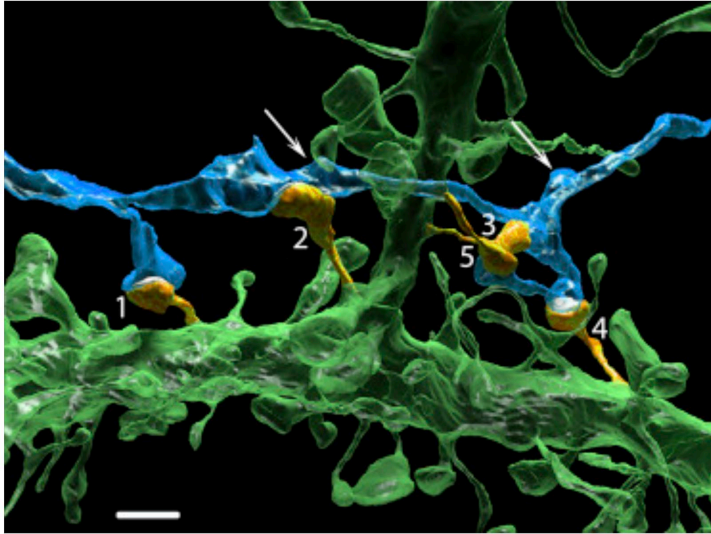
- Multiple information carrier
- Low energy consumption
- In-memory computing
- Hardware-level plasticity
- Good biocompatibility
- ...

Potentials

- Brain-like computing
- Brain-computer interface
- Neurological disease treatment
- ...

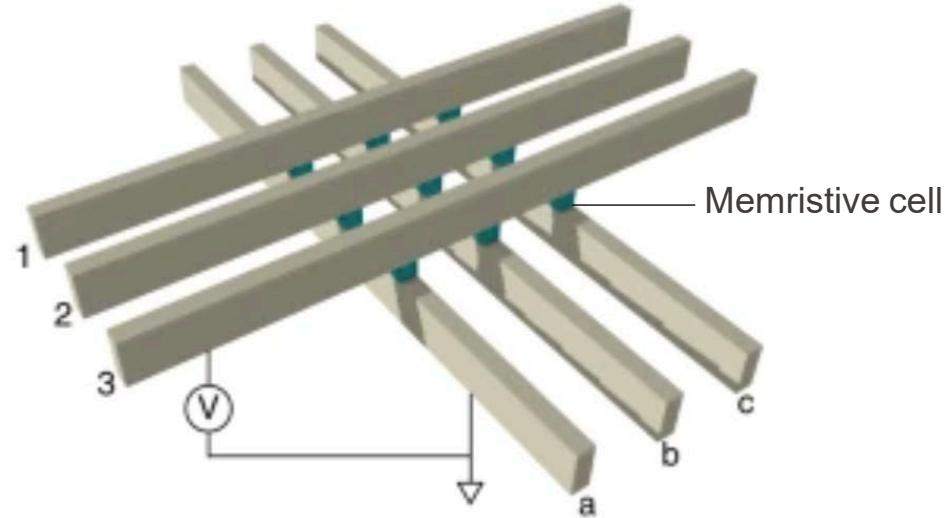
Trends: ion channel-like → synapse-like → neural network-like → brain-like

N. Kasthuri et al. Cell. 2015



Biological neural network
Ions as information carrier

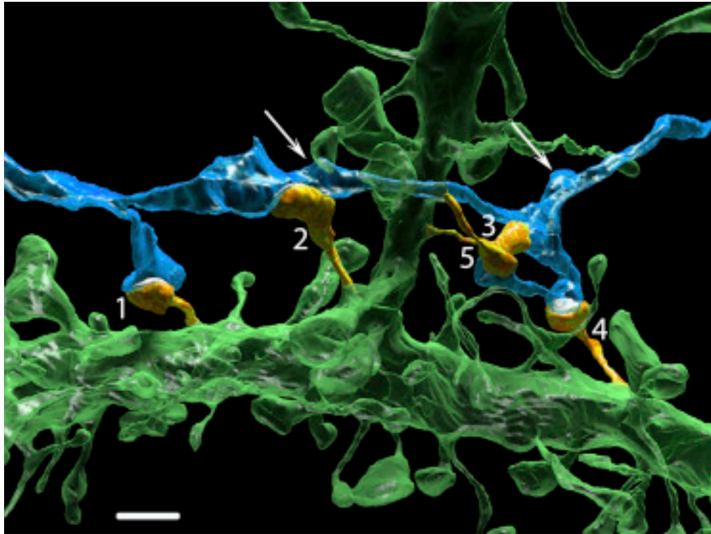
Shuang Pi et al. Nature Nanotechnology. 2019



Artificial neural network (ANN)
electrons as information carrier

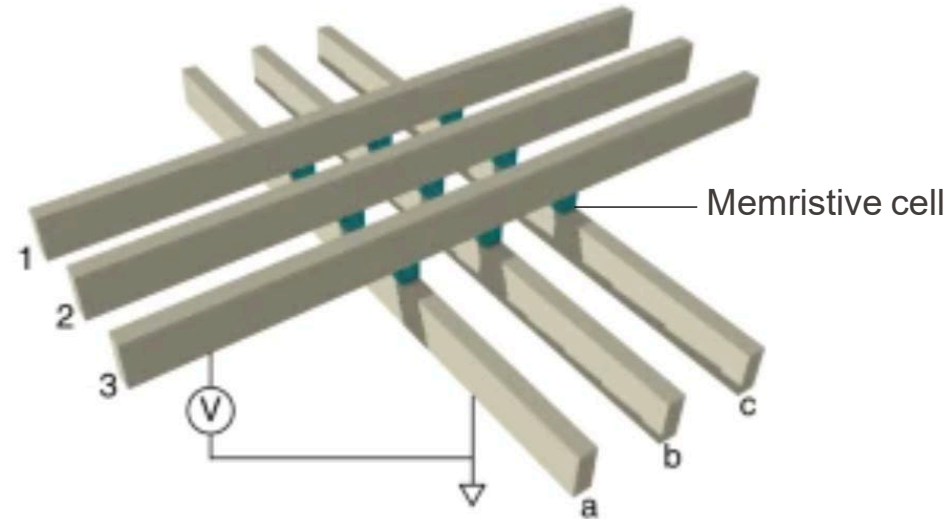
Need ionic ANN for accurate biomimicking

N. Kasthuri et al. Cell. 2015



Biological neural network
Ions as information carrier

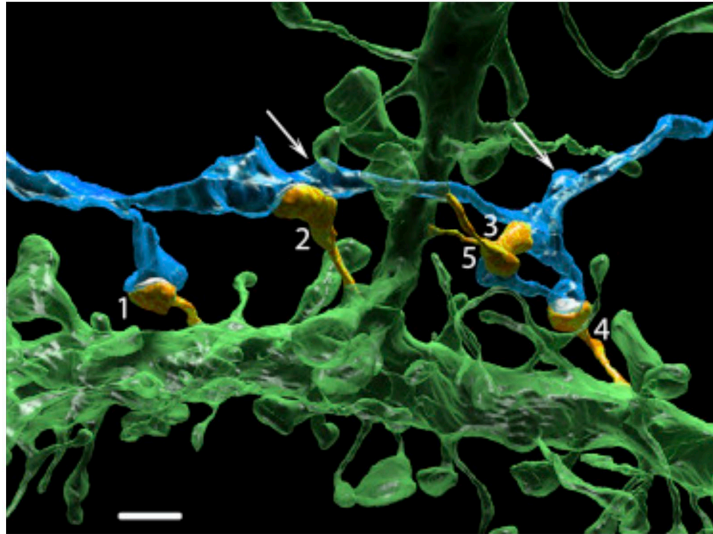
Shuang Pi et al. Nature Nanotechnology. 2019



Artificial neural network (ANN)
electrons as information carrier

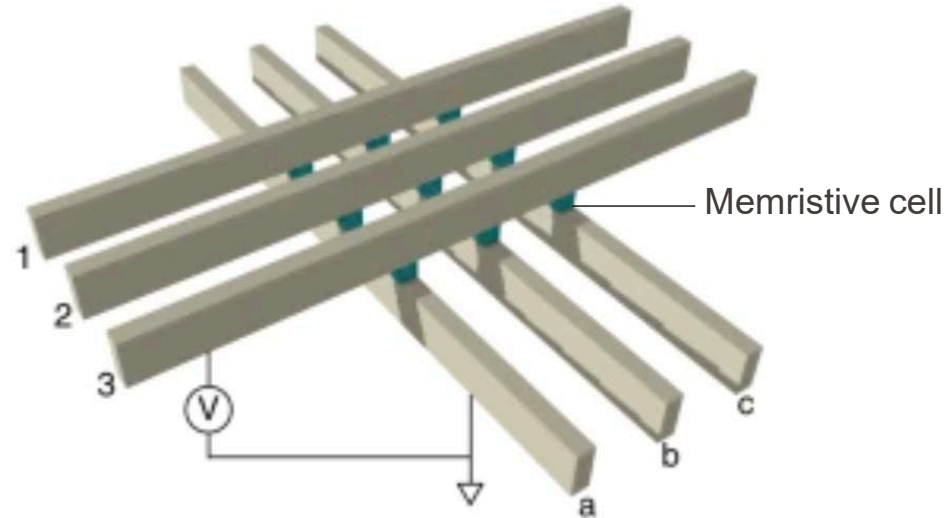
Need ionic ANN for accurate biomimicking

N. Kasthuri et al. Cell. 2015



Biological neural network
Ions as information carrier

Shuang Pi et al. Nature Nanotechnology. 2019



Artificial neural network (ANN)
electrons as information carrier

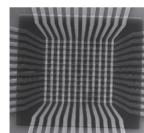
Need ionic ANN for accurate biomimicking



Leon O. Chua
concept of
memristor

The idea of
brain-like
computing

Hebbian
Learn Rule



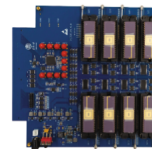
Memristor array
(12x12, Analog)



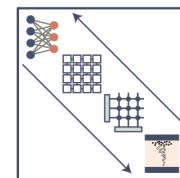
Memristor macro
(1 Mb, Digital)



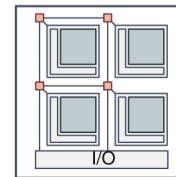
Fully memristor
chip
(160 kb, Analog)



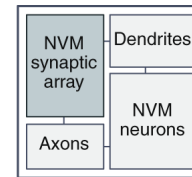
Fully memristor
system
(16 kb, Analog)



Codesign
EDA tool chain

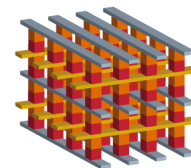


General-purpose
NVM based chip

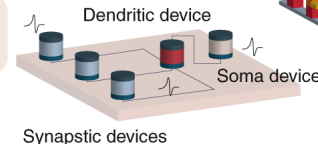


'Brain' chip

3D integration technology

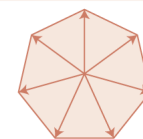


Neuromorphic devices and
integration technology



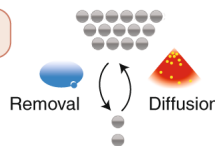
Synaptic devices

Optimized performance
meet application
requirements



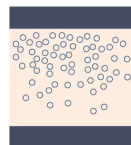
2T2R + 3T1C
Unit cell

Diffusive memristor

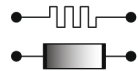


Removal
Diffusion

Analogue memristor



Device linked to
memristor

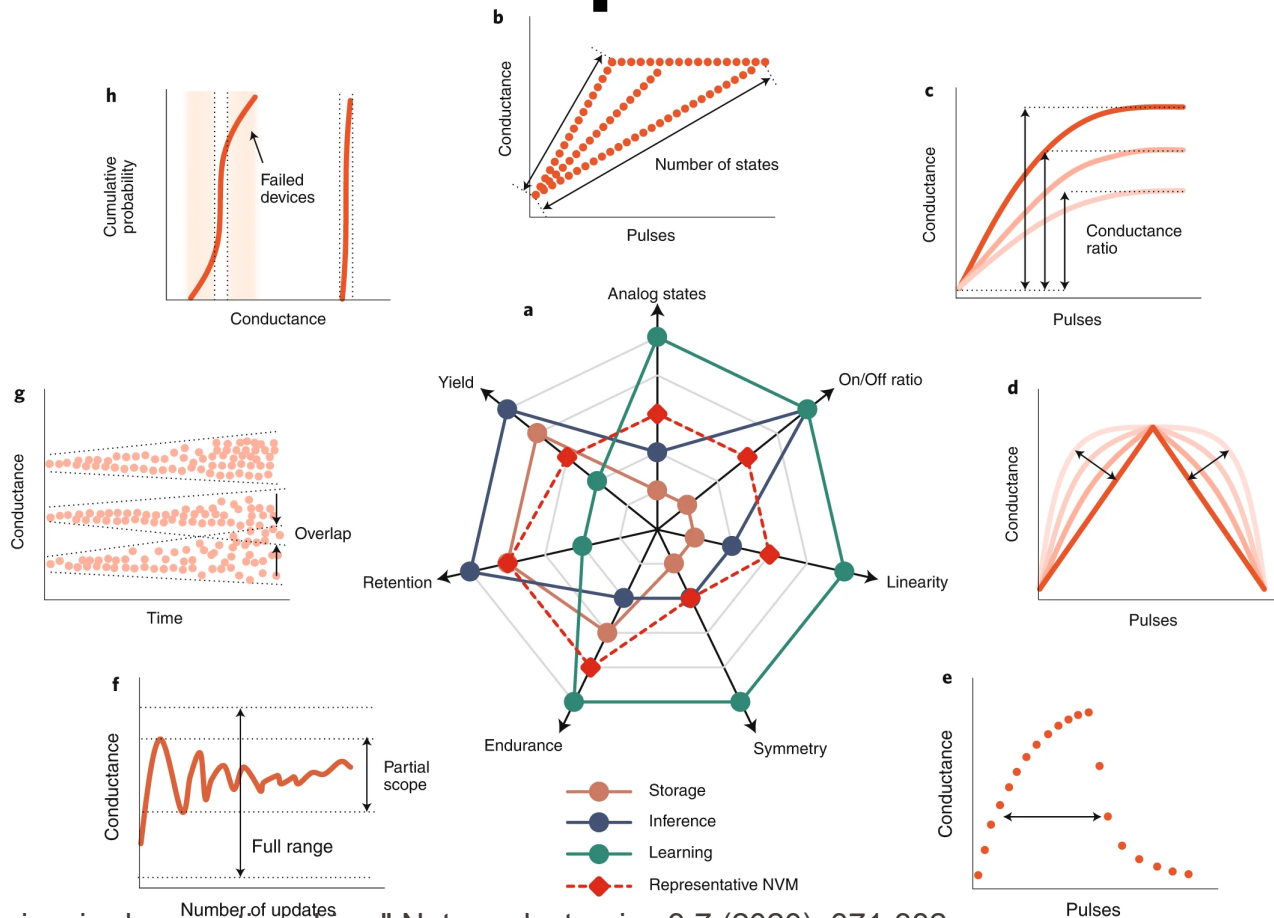


Chip and system
5+ years
Device and technology

10+ years

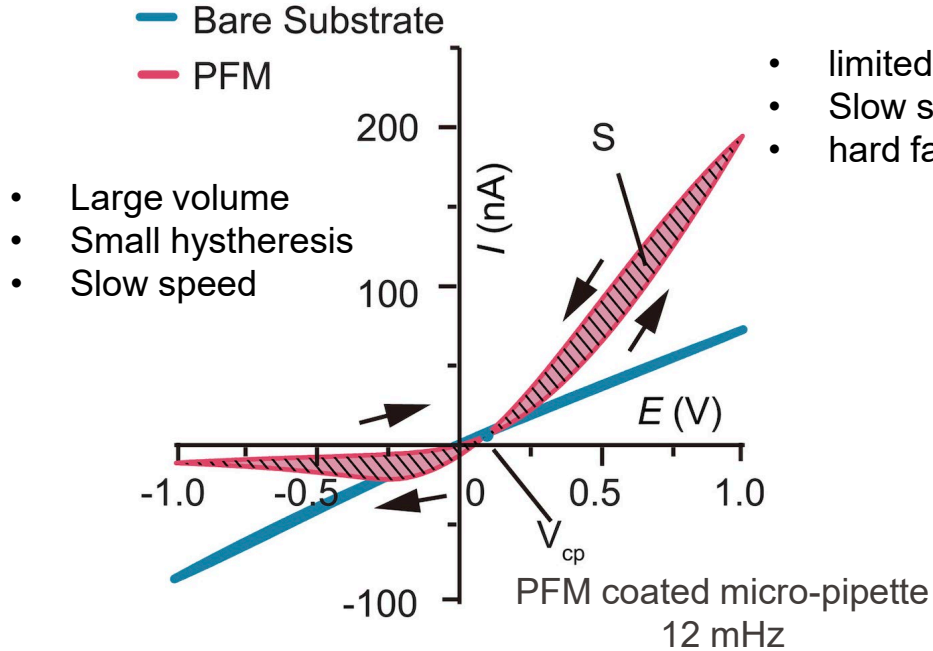
Zhang, Wenqiang, et al. "Neuro-inspired computing chips." *Nature electronics* 3.7 (2020): 371-382.

- Ion migration materials
- Phase change materials
- Conductive filament-based materials
- Magnetics
- Ferroelectrics
- 2D materials

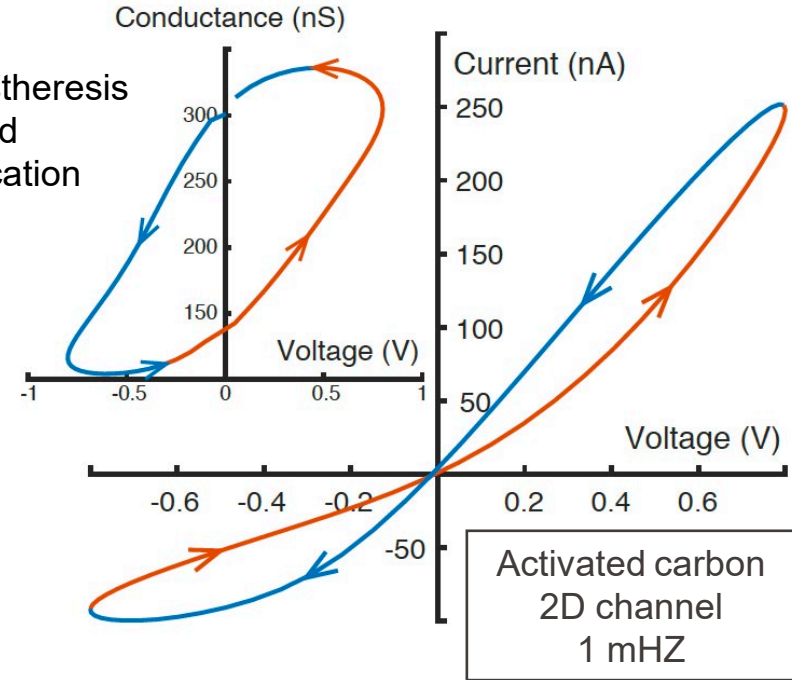


- Zhang, Wenqiang, et al. "Neuro-inspired computing chips." *Nature electronics* 3.7 (2020): 371-382.

Limitations of fluidic memristors



- limited hysteresis
- Slow speed
- hard fabrication



T. Xiong *et al.* *Science*. 2023

P. Robin*, T. Emmerich*, A. Ismail* *et al.* *Science*. 2023

**Need for a compact, performant, reliable, and scalable device to build ionic ANN
and move forward iontronics**

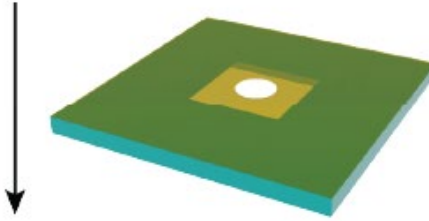
Logic: a new device for network scale iontronics-HACs⁴⁶

Fast and scalable fab:

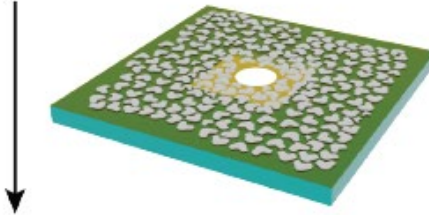
10s of devices per week

**Most of the steps at
Wafer-scale production**

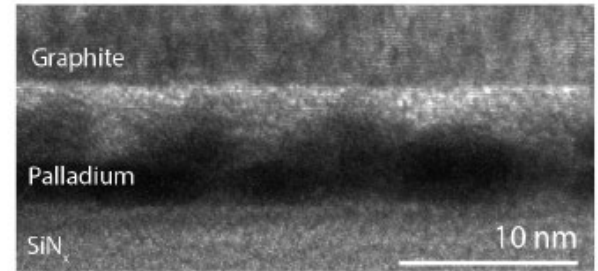
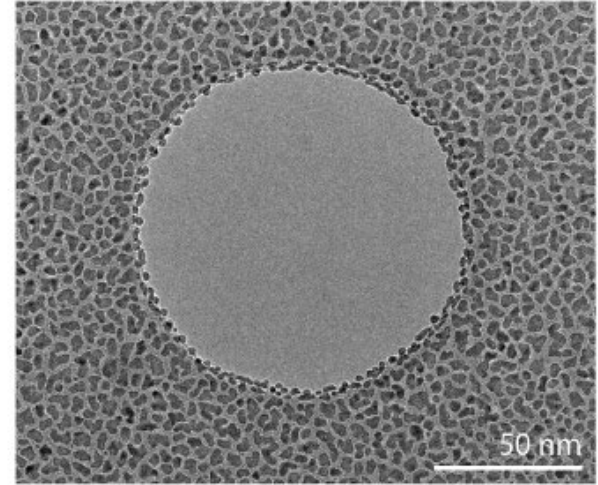
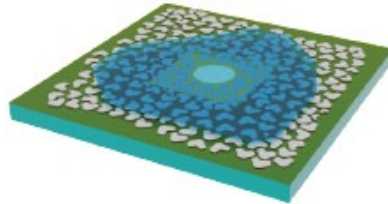
Step 0: Silicon nitride membrane (Wafer scale)



Step 1: Palladium deposition (Wafer scale)



Step 2: Graphite transfer (Chip scale)



■ Ionic logic with highly asymmetric nanofluidic memristive switches Emmerich*, Teng*, Ronceray *,Radenovic* <https://arxiv.org/abs/2306.07617>

Logic: a new device for network scale iontronics-HACs⁴⁷

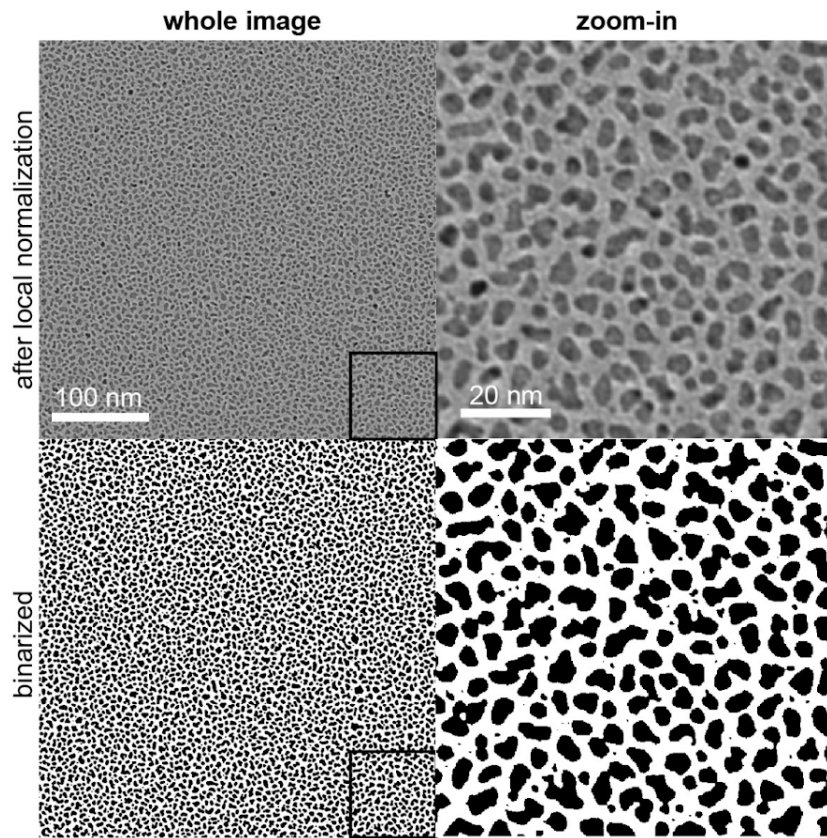
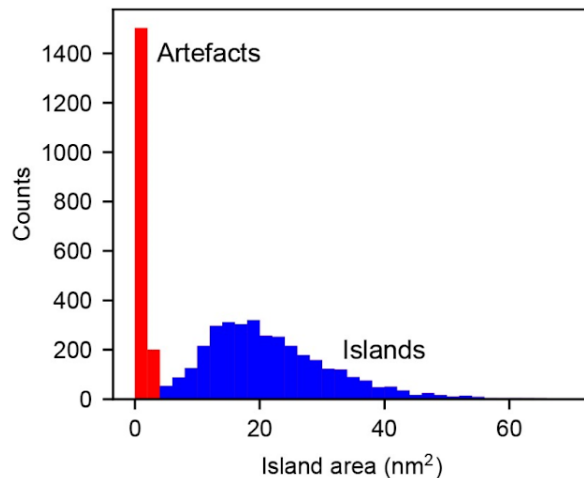


Image processing steps:

- Local normalization (10 nm window)
- Gaussian blur (sigma = 0.6 nm)
- Binarize (threshold: equidistant from peaks)



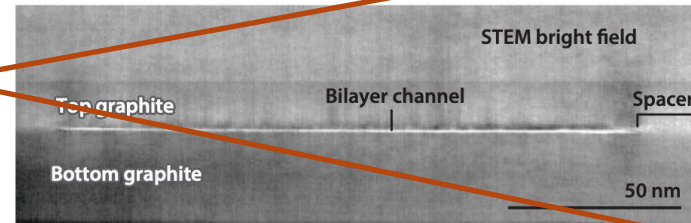
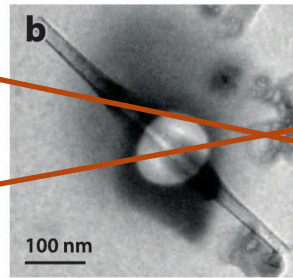
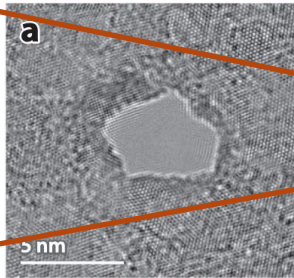
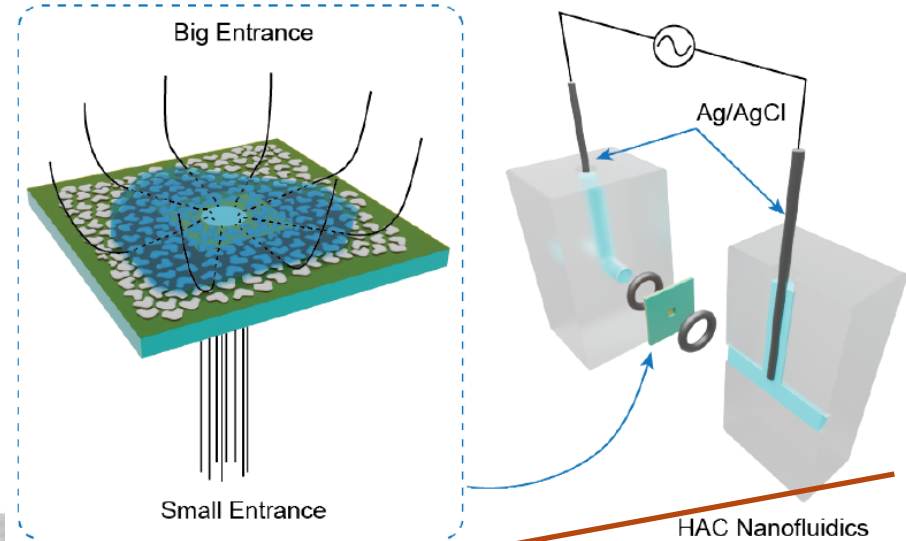
Island coverage 45%

Mean Island area 22nm

Ionic logic with highly asymmetric nanofluidic memristive switches

■ Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>

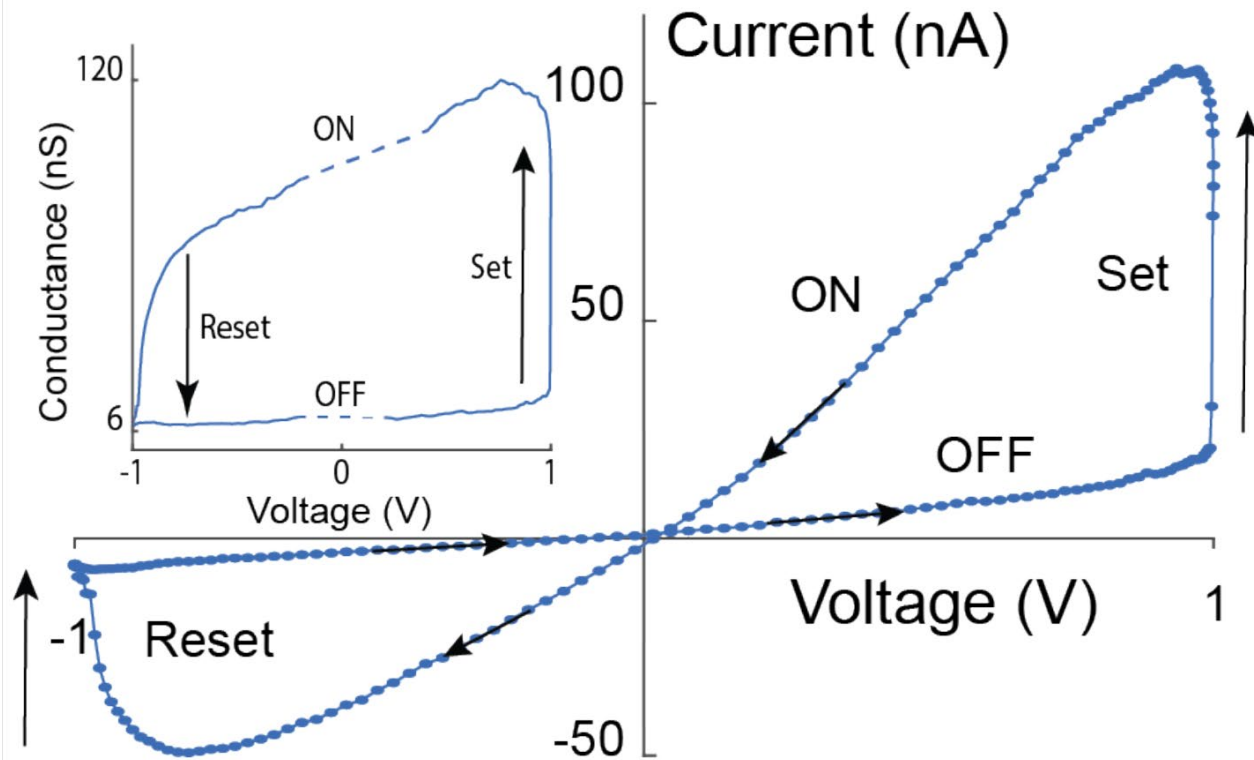
Combination of giant aspect ratio (100s fold) between both entrances and single-digit confinement in the presence of a charged material



Performances 2 orders of magnitude better than previous report
unique discontinuous behavior (threshold for abrupt switching)

1M KCl

50 mHz



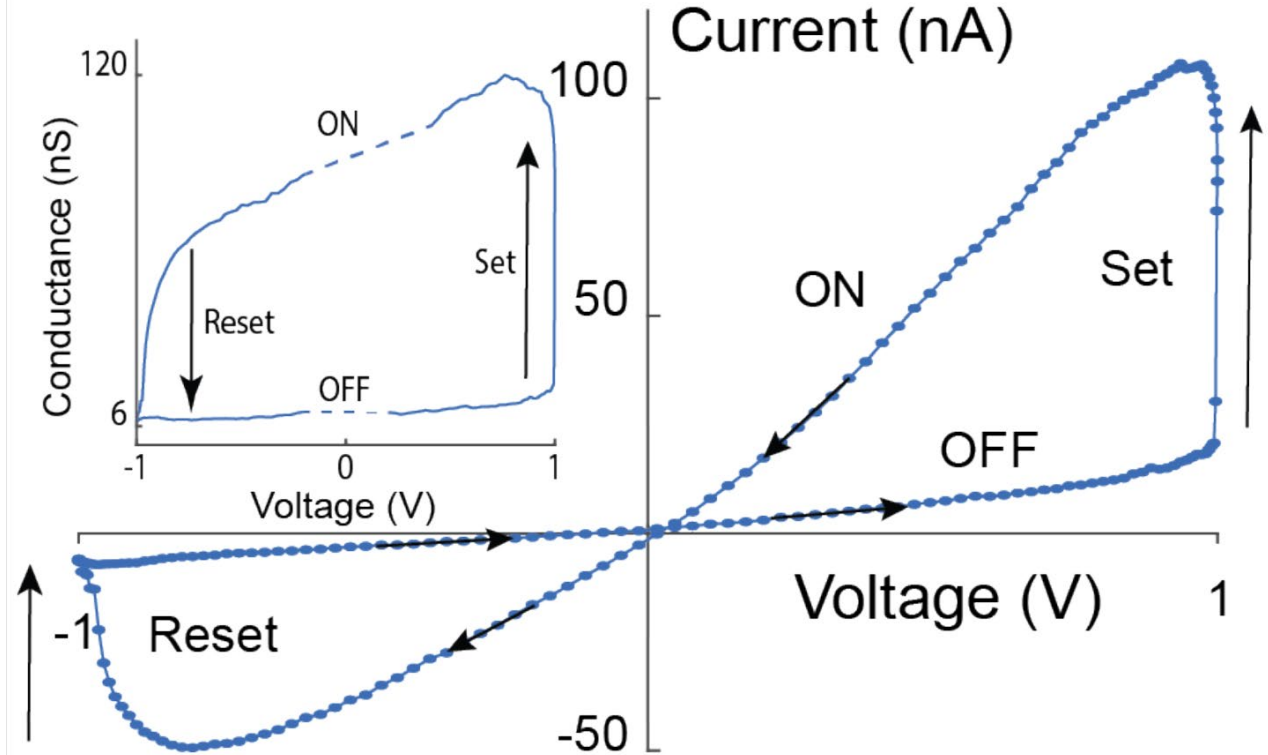
Ionic logic with highly asymmetric nanofluidic memristive switches

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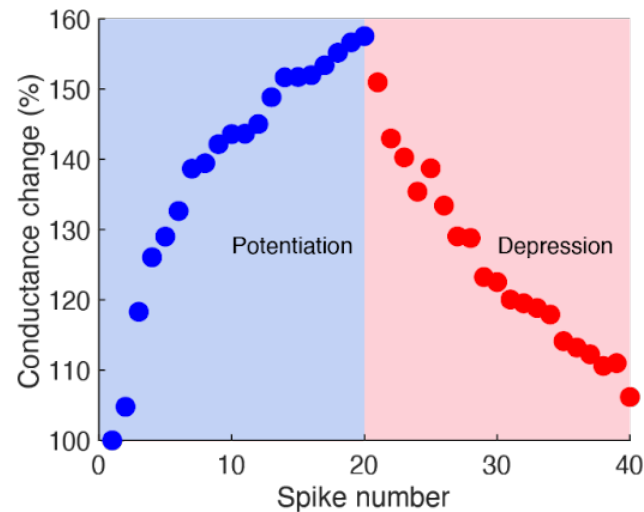
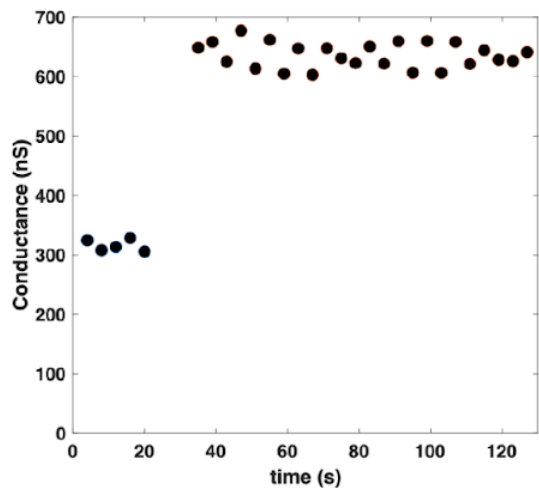
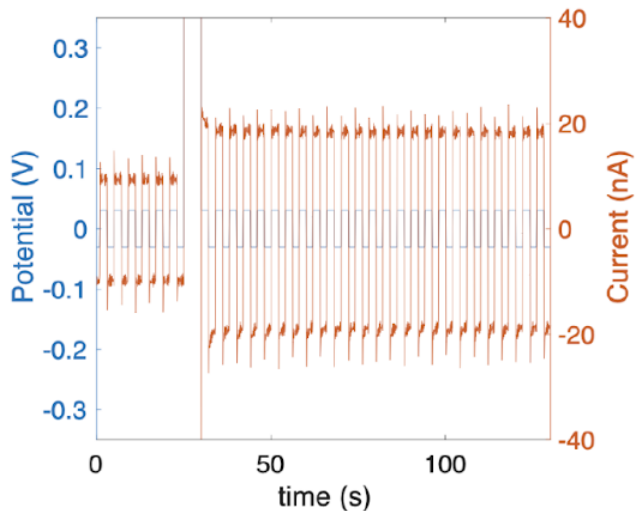


Ionic logic with highly asymmetric nanofluidic memristive switches

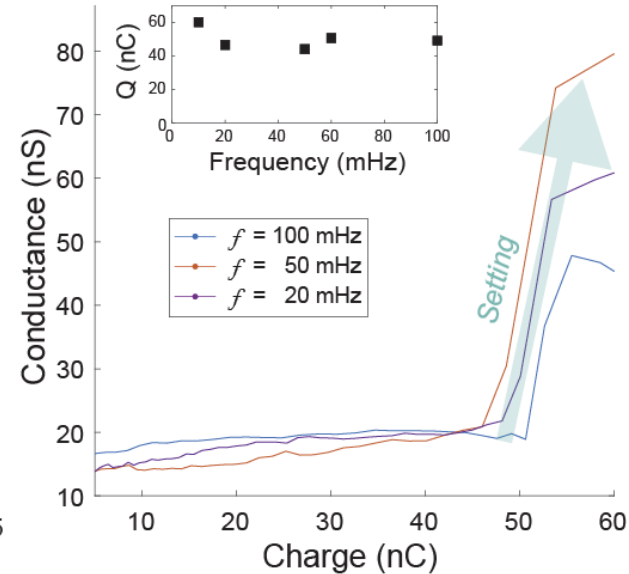
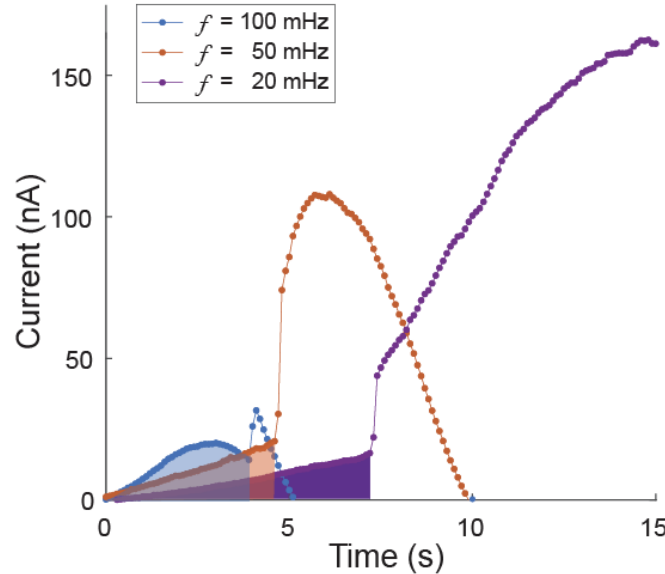
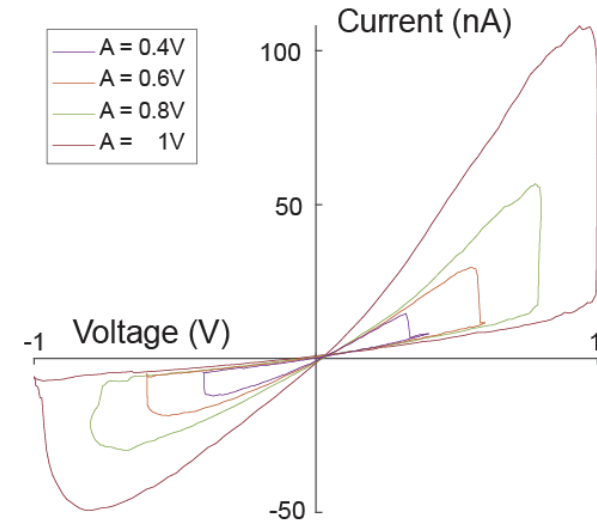
Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>

long term potentiation

- The device is set with a single positive voltage pulse of 1V
- The conductance is measured with voltage pulse train oscillating between plus and minus 30 mV..



Not a voltage threshold

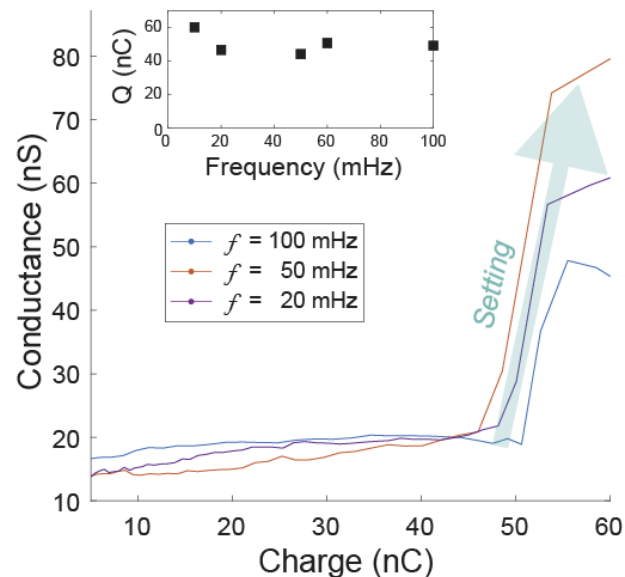
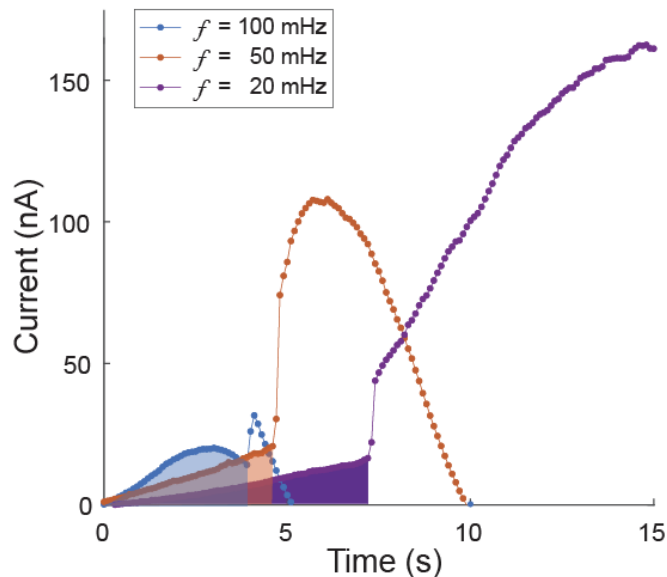
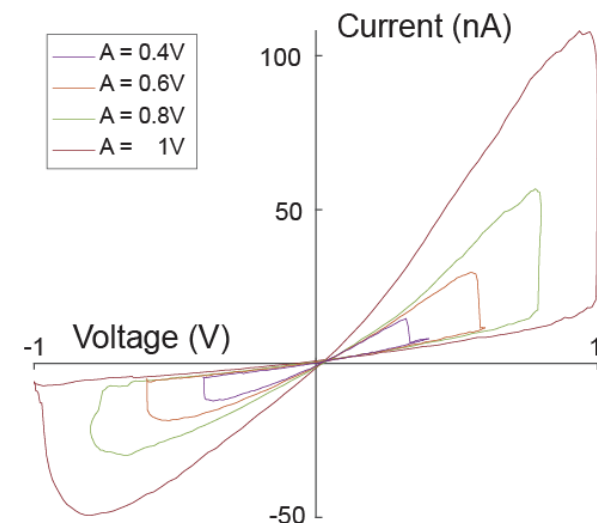


When a given amount of ions has flown through the device switching occurs

Charge threshold

- Ionic logic with highly asymmetric nanofluidic memristive switches
Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>

Not a voltage threshold



When a given amount of ions has flown through the device switching occurs.....

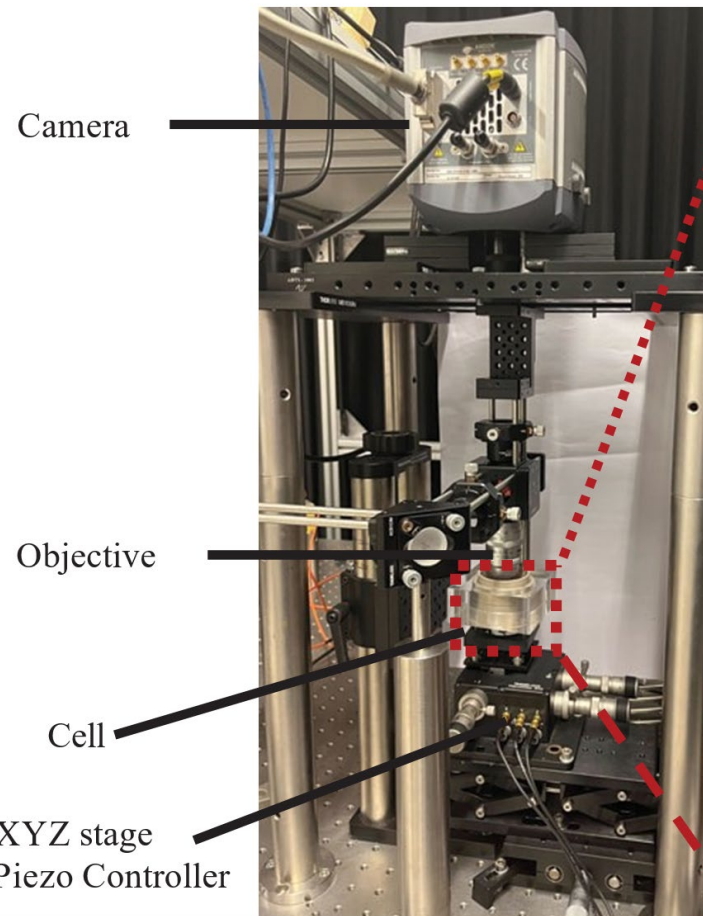
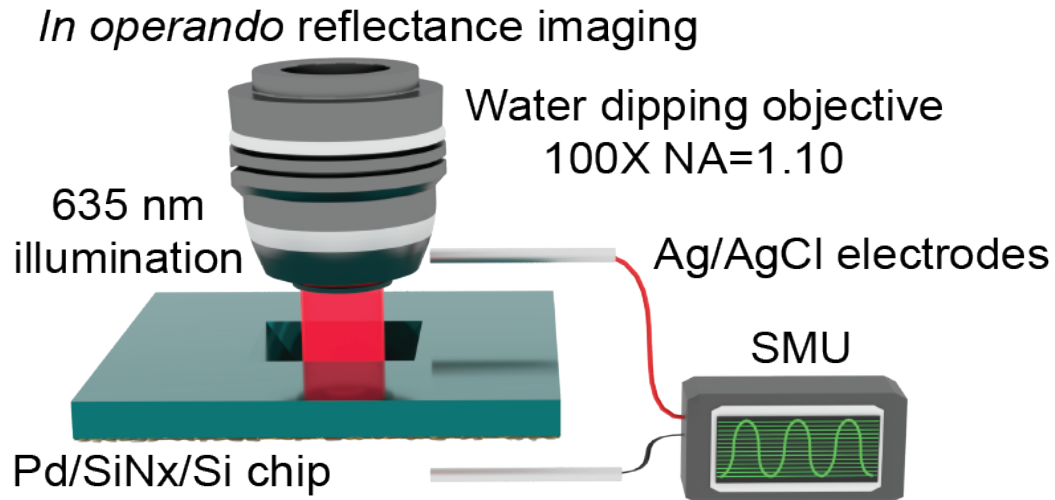
Charge threshold

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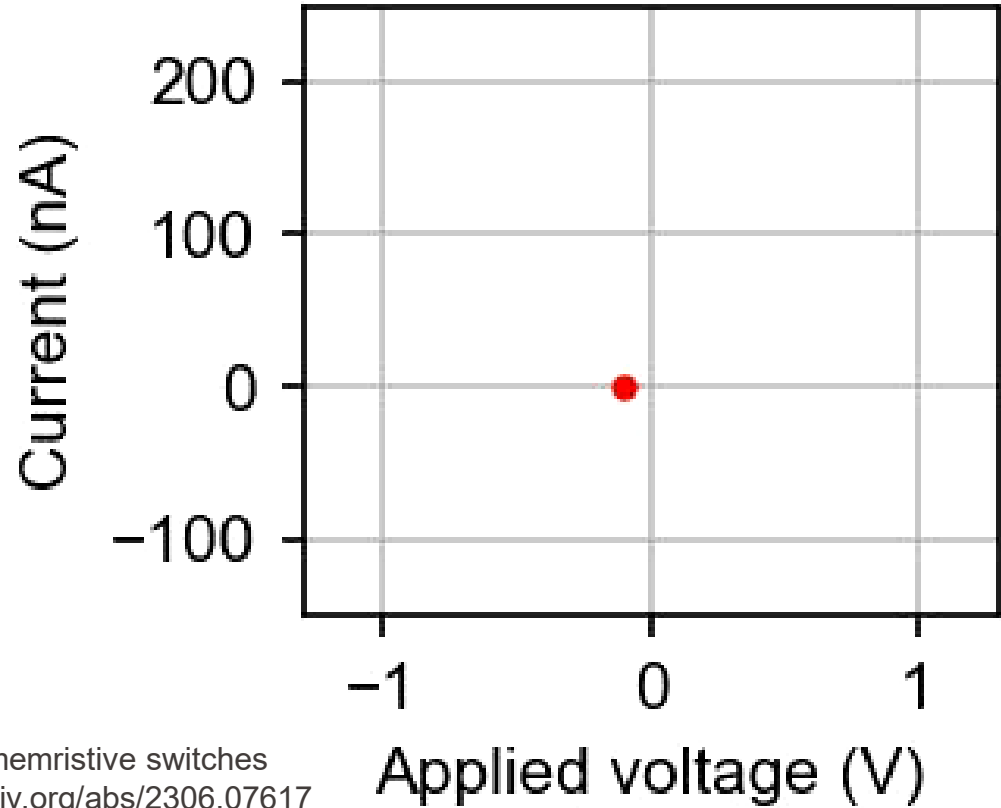
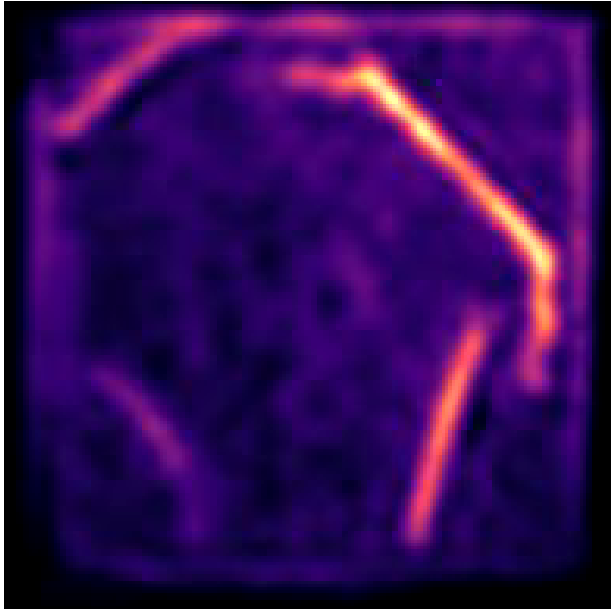


“You can **observe** a lot
by **watching**.”

- *Yogi Berra*

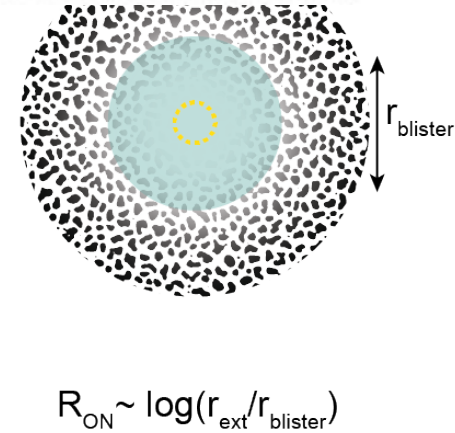
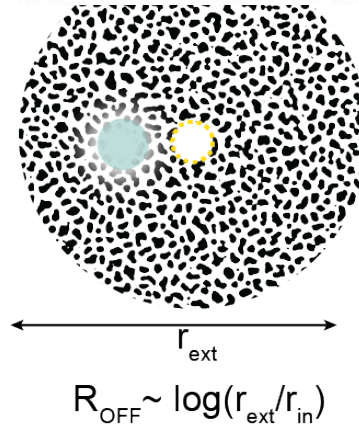
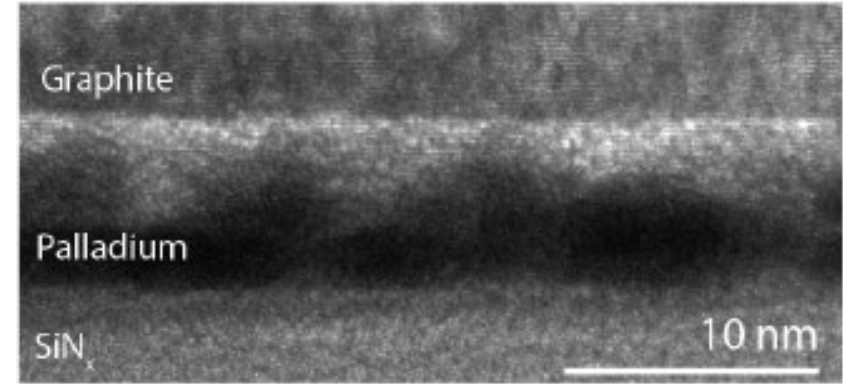
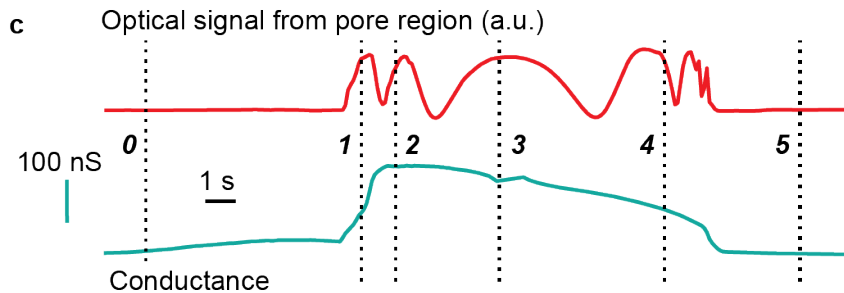
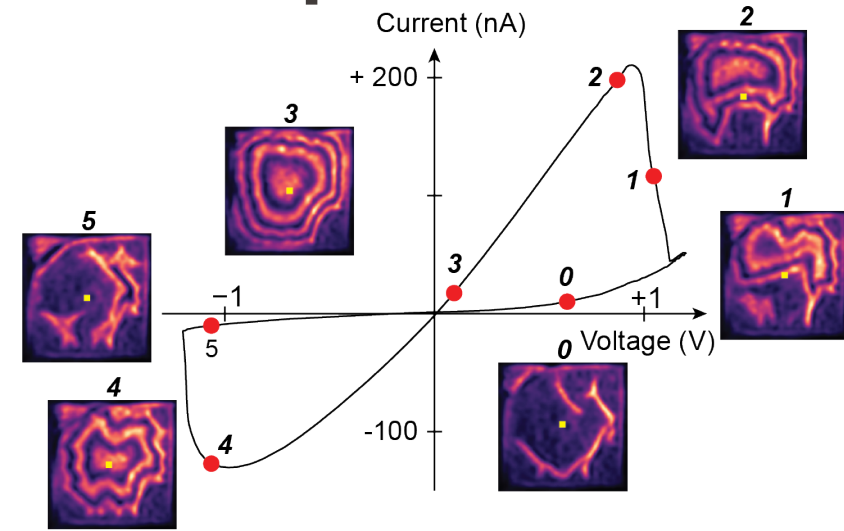


Ionic logic with highly asymmetric nanofluidic memristive switches with Piezo Controller
Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>



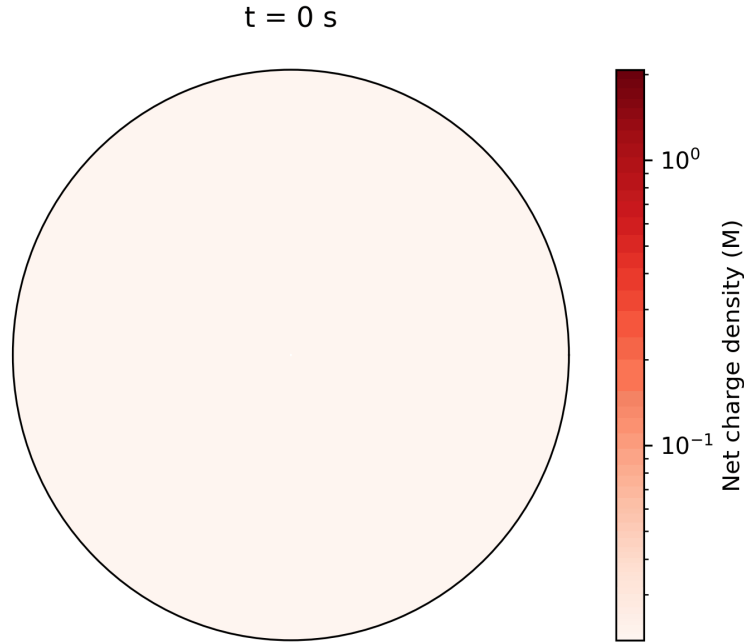
Ionic logic with highly asymmetric nanofluidic memristive switches
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Proposed mechanism ionic transport in HACs

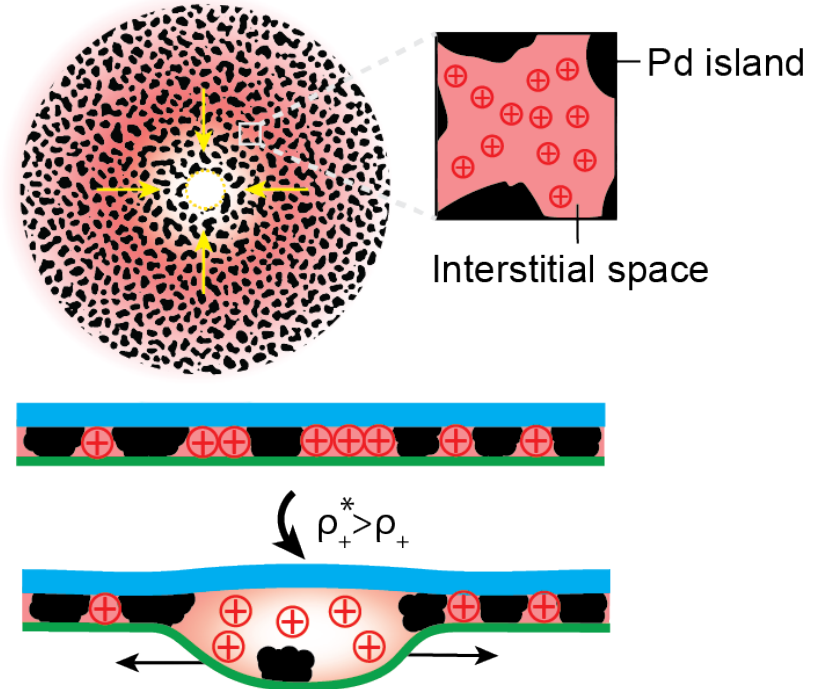


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Proposed mechanism ionic transport in HACs

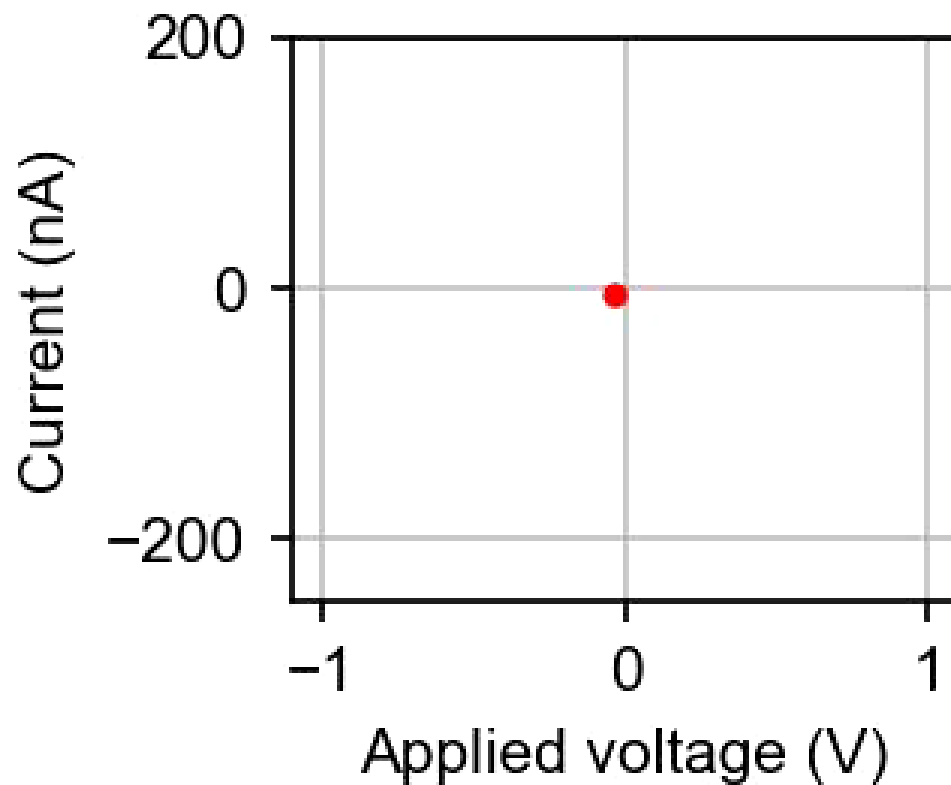
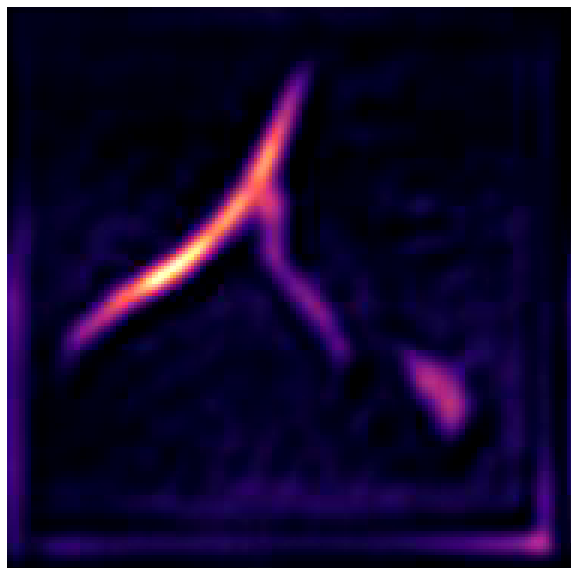


Charge focusing induces blister formation



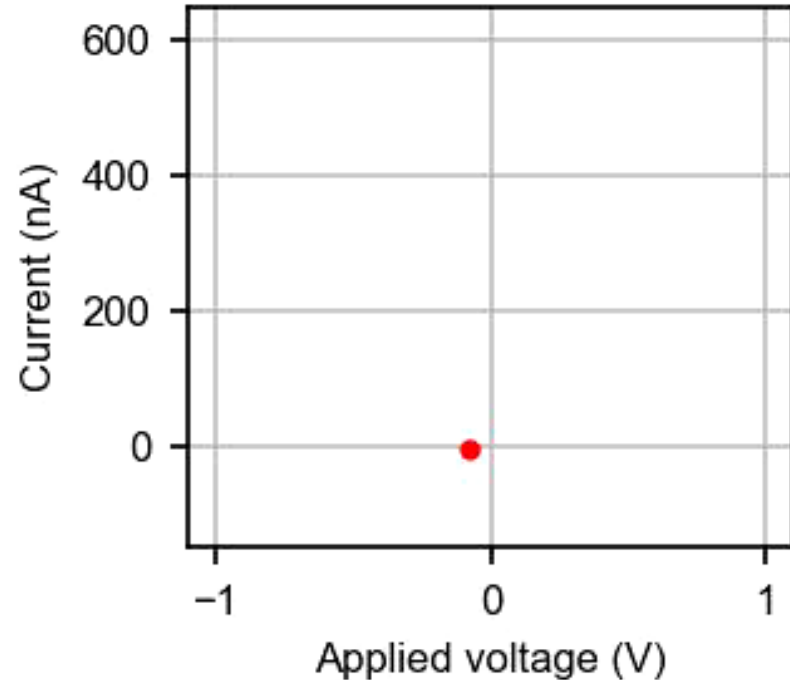
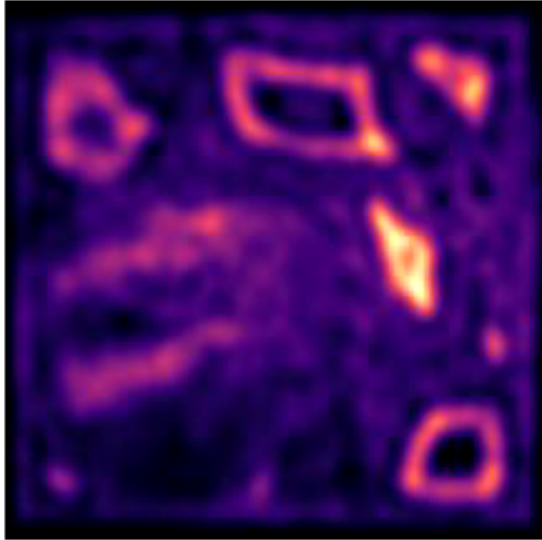
Graphite 100 mC/cm²

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300 mHz - Repeatability over 17 cycles

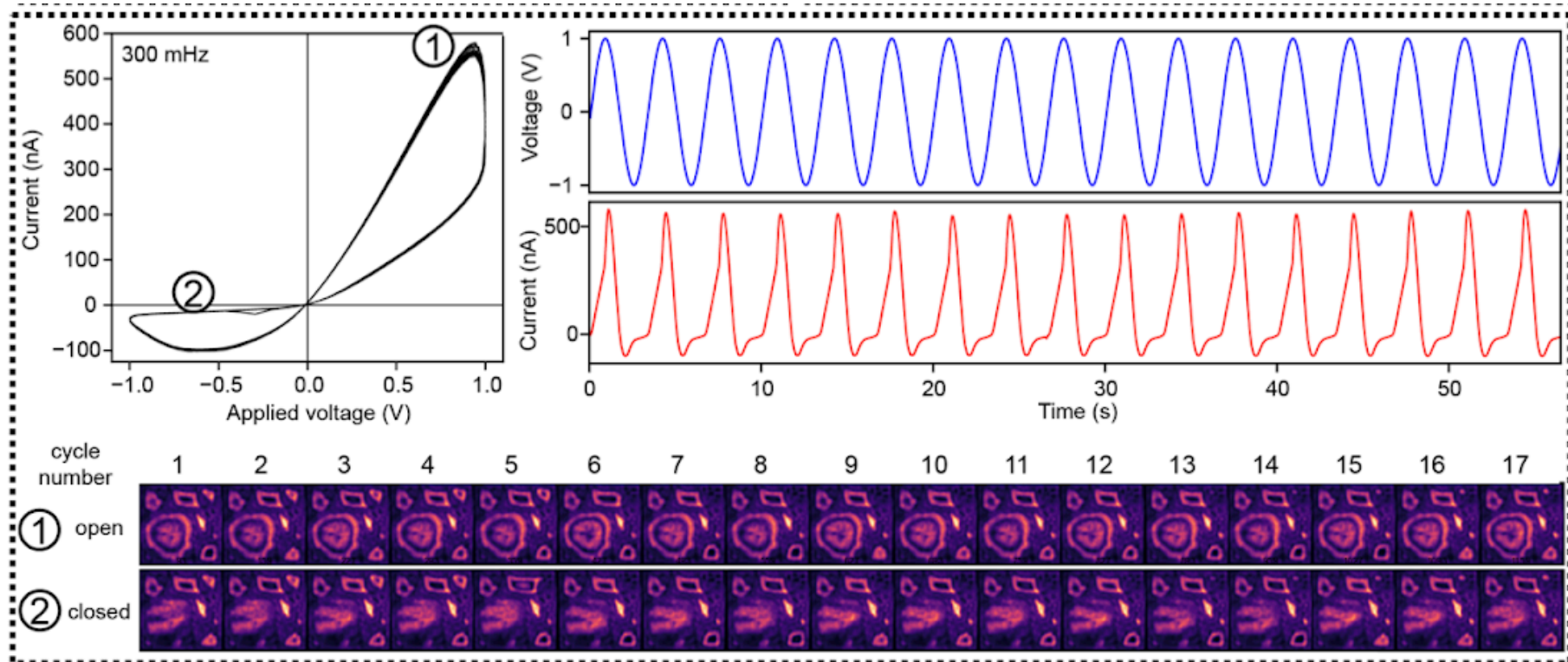
- blister bridges the pore to somewhere closer to the outer region



Endurance measurements

300 mHz - Repeatability over 17 cycles

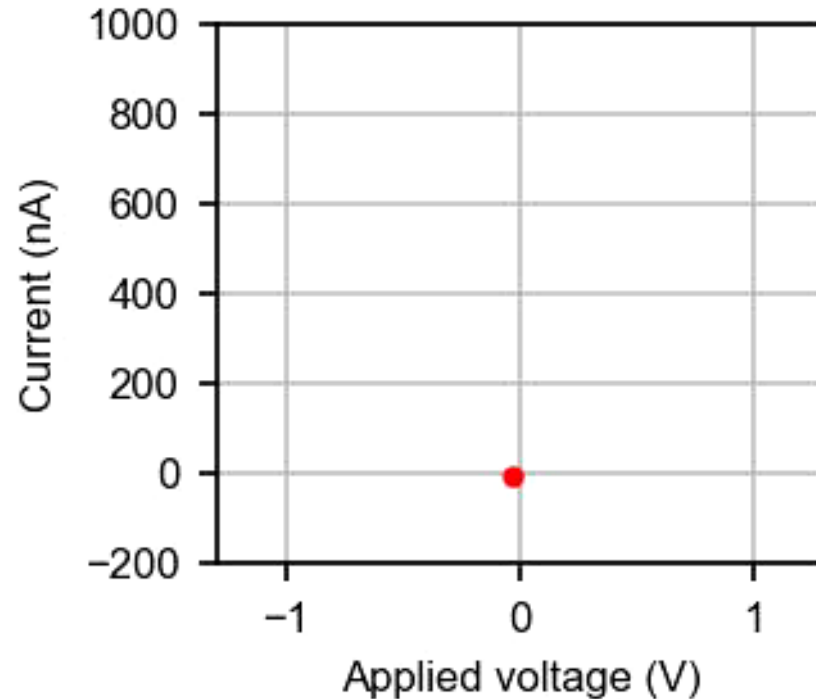
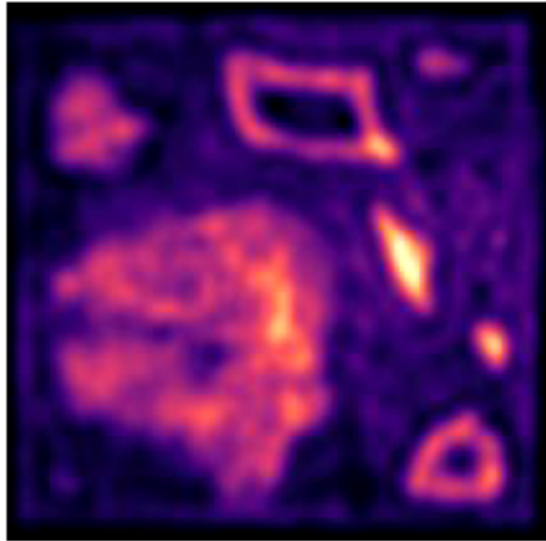
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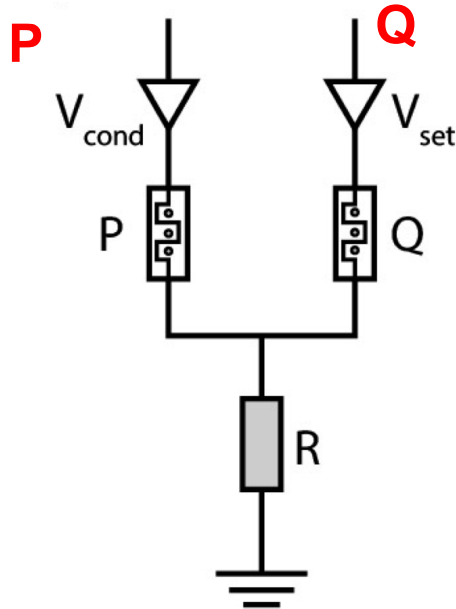
Endurance measurements

300 mHz – Voltage ramp from 0.2 to 1.2 V

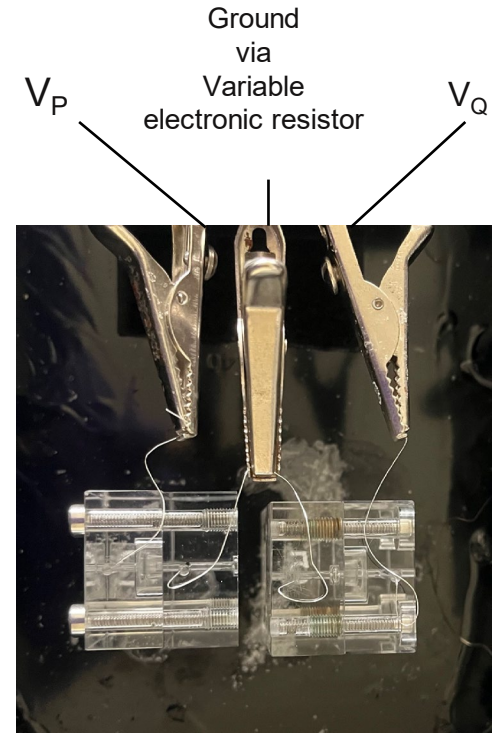
blister bridges the pore to somewhere closer to the outer region



LETTERS

'Memristive' switches enable 'stateful' logic operations via material implicationJulien Borghetti¹, Gregory S. Snider¹, Philip J. Kuekes¹, J. Joshua Yang¹, Duncan R. Stewart^{1†} & R. Stanley Williams¹

First ionic computing experiment with channels communicating with each other the material implication (IMP) logic gate



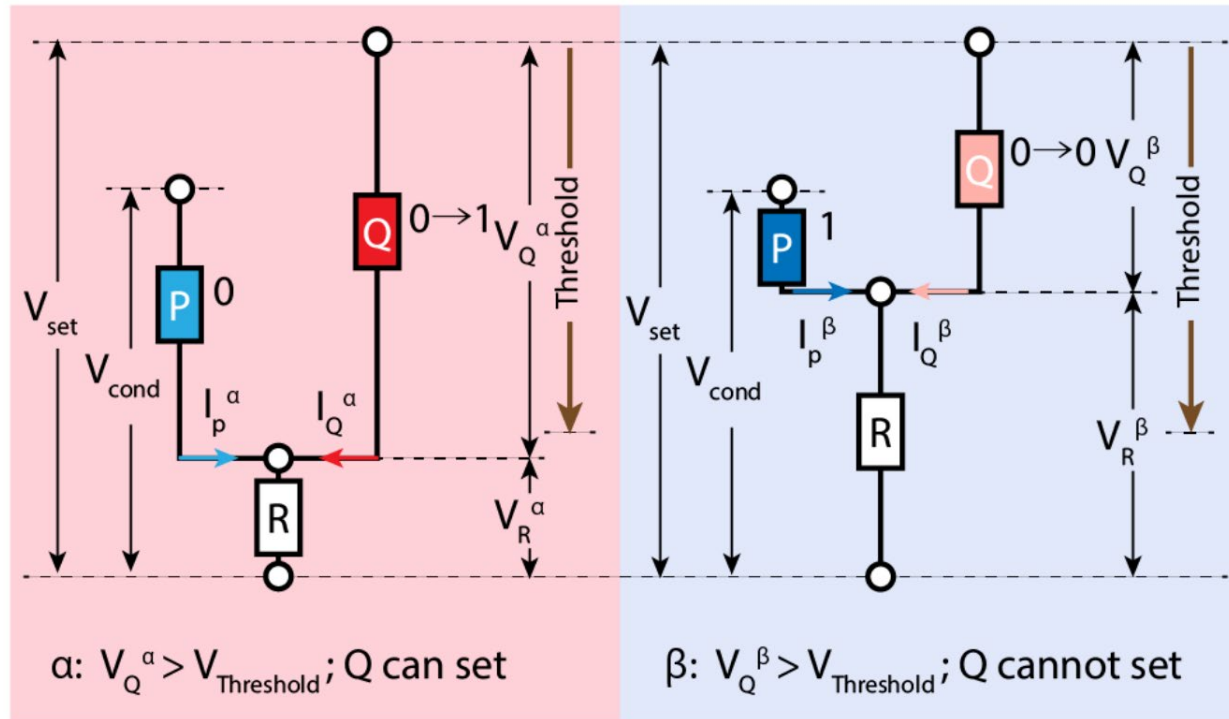
Ionic logic with highly asymmetric nanofluidic memristive switches

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IMP gate can be implemented with two memristive switches

Set Q only if P is off

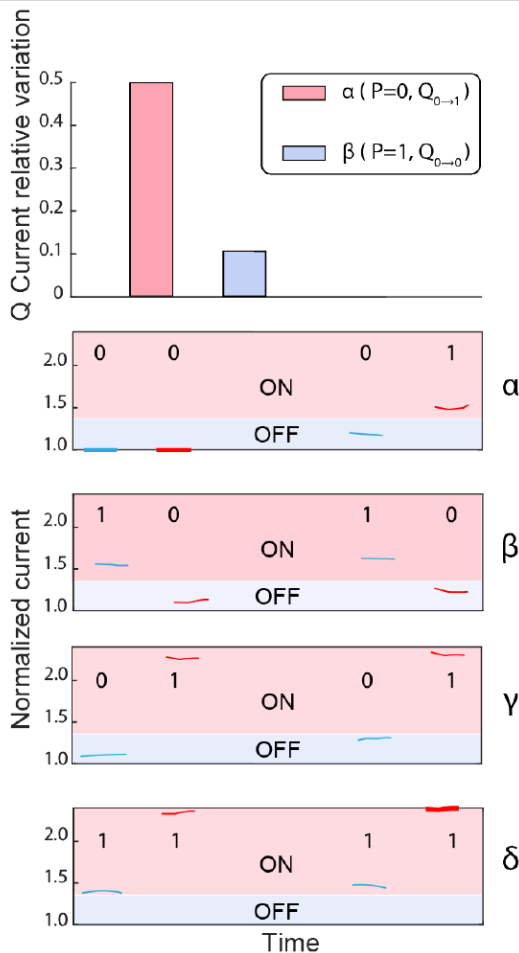
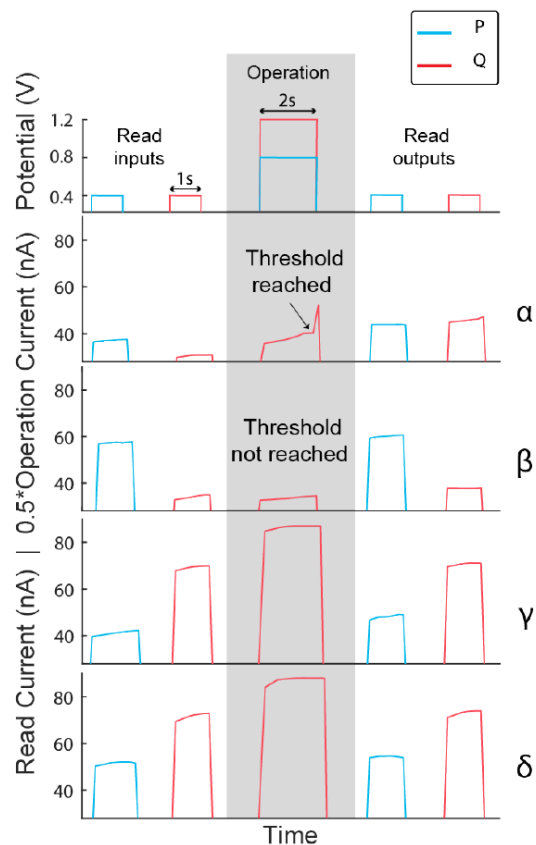
Case	P	Q	P'	Q'
α	0	0	0	1
β	1	0	1	0
γ	0	1	0	1
δ	1	1	1	1



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Logic: Results



1M KCl

65

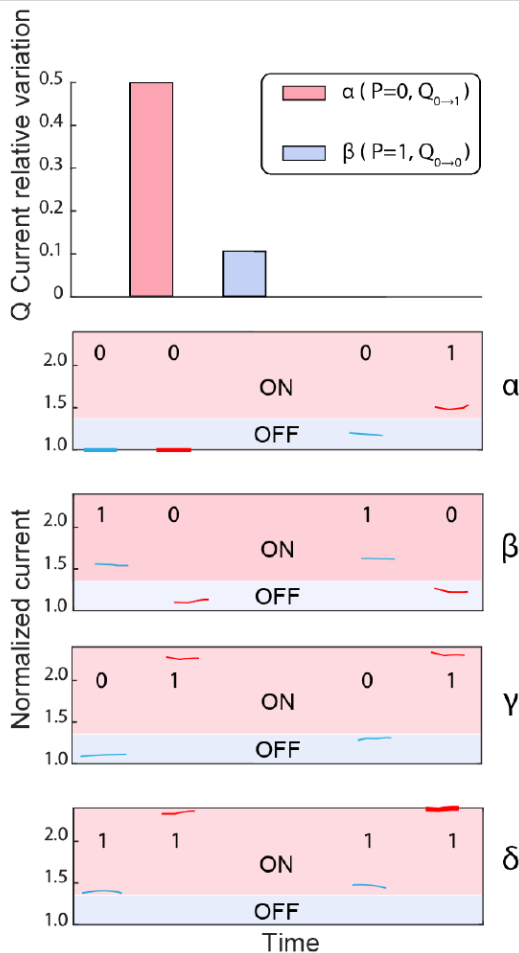
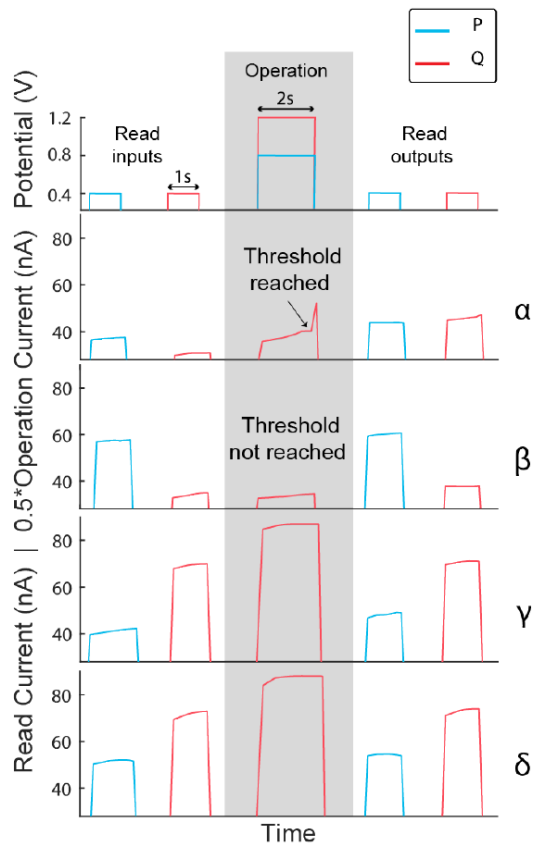
**IMP logic successfully
implemented with two HACs**

$$V_R^\alpha = R(I_P^\alpha + I_Q^\alpha)$$

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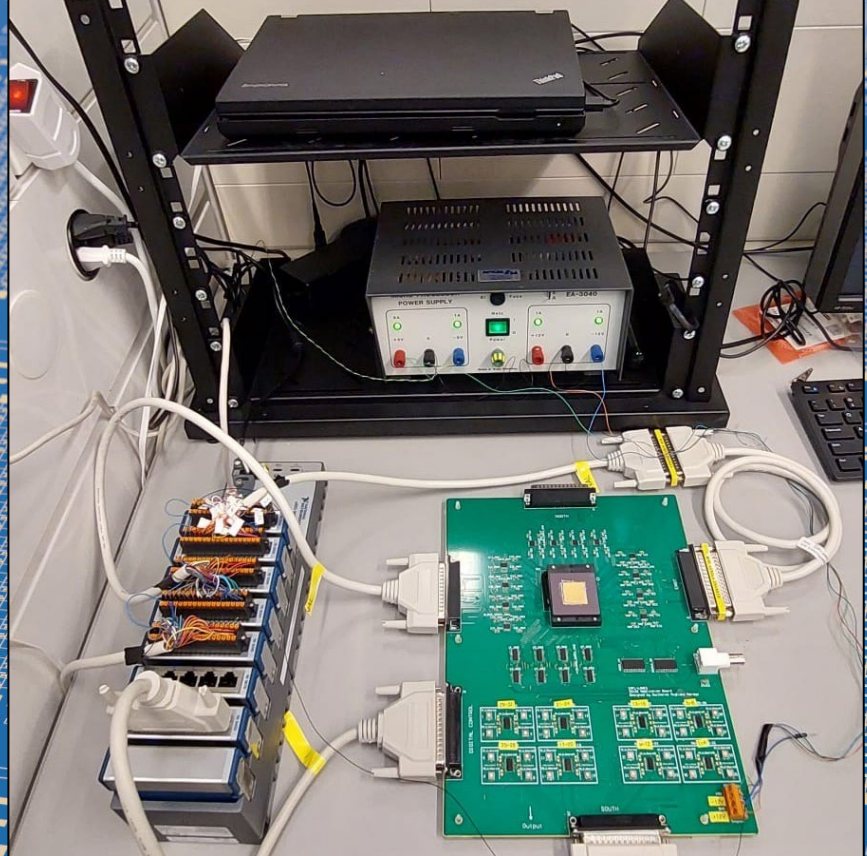
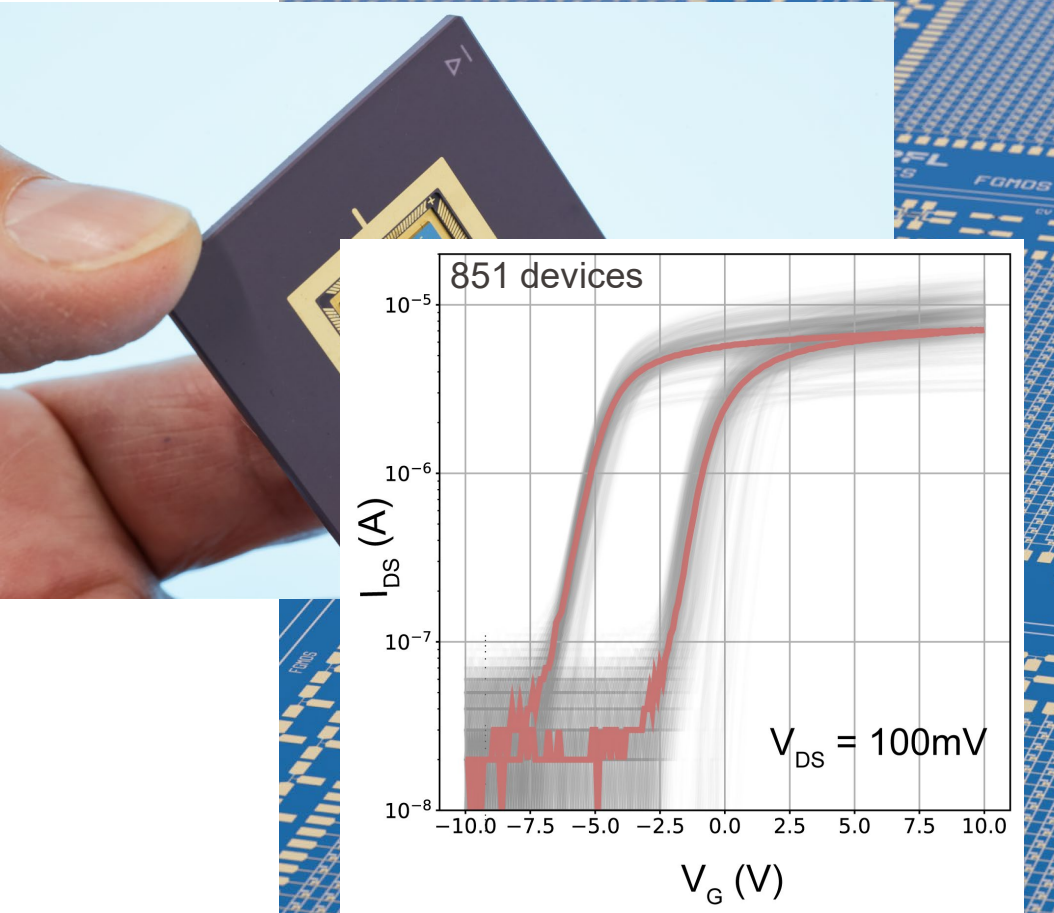
**IMP logic successfully
implemented with two HACs**

$$V_R^\alpha = R(I_P^\alpha + I_Q^\alpha)$$

$$R_{set} < R < R_{cond}$$

Ionic logic with highly asymmetric nanofluidic memristive switches

Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>



Marega...Kis;
arXiv:2303.07183

- **HACs exhibit excellent scalability, speed, and conductance ratio**
- **Direct imaging of the mechano-ionic memory mechanism with in-operando optical observation –will guide the device optimization**
- **Logic circuits with two HACs working simultaneously have been successfully assembled**
- **Future efforts should focus on connecting HACs with water channels to create fully liquid circuits.**

Ionic logic with highly asymmetric nanofluidic memristive switches

- Emmerich*, Teng*,Radenovic* <https://arxiv.org/abs/2306.07617>